

Silicon Detectors for Precision Tracking

LTP Seminar

Paul Scherrer Institute

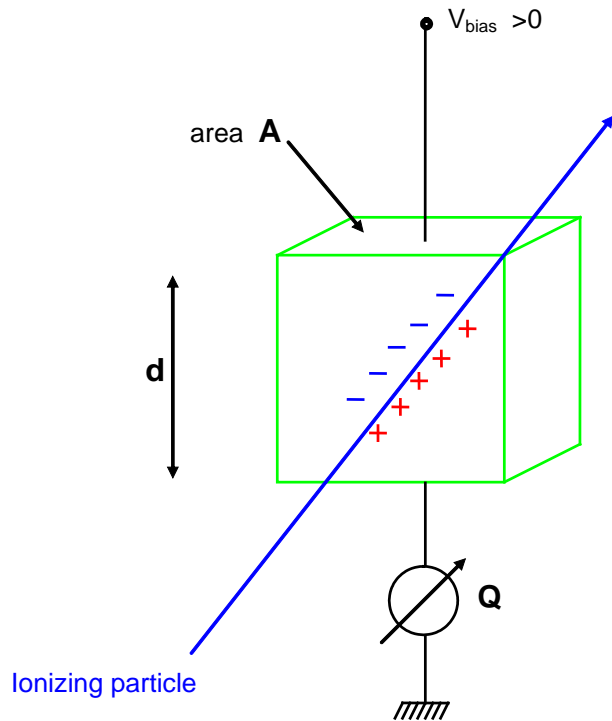
10. July 2017

Roland Horisberger

„Ohmic“ Particle Detector

(Gedankenexperiment)

Ohmic material : Resistivity ρ



• **E-field** :

$$E = V_{\text{bias}} / d$$

• **Carrier velocity** :

$$v = \mu E = \mu (V_{\text{bias}} / d)$$

• **Signal collection time** :

$$\tau = d / v = d^2 / (\mu V_{\text{bias}})$$

• **Resistance** :

$$R = \rho (d / A)$$

• **„leakage current“** :

$$i_{\text{leak}} = V_{\text{bias}} / R = (V_{\text{bias}} A) / (\rho d)$$

• **„leakage charge“** :

$$Q_{\text{leak}} = i_{\text{leak}} \tau = d A / \rho \mu$$

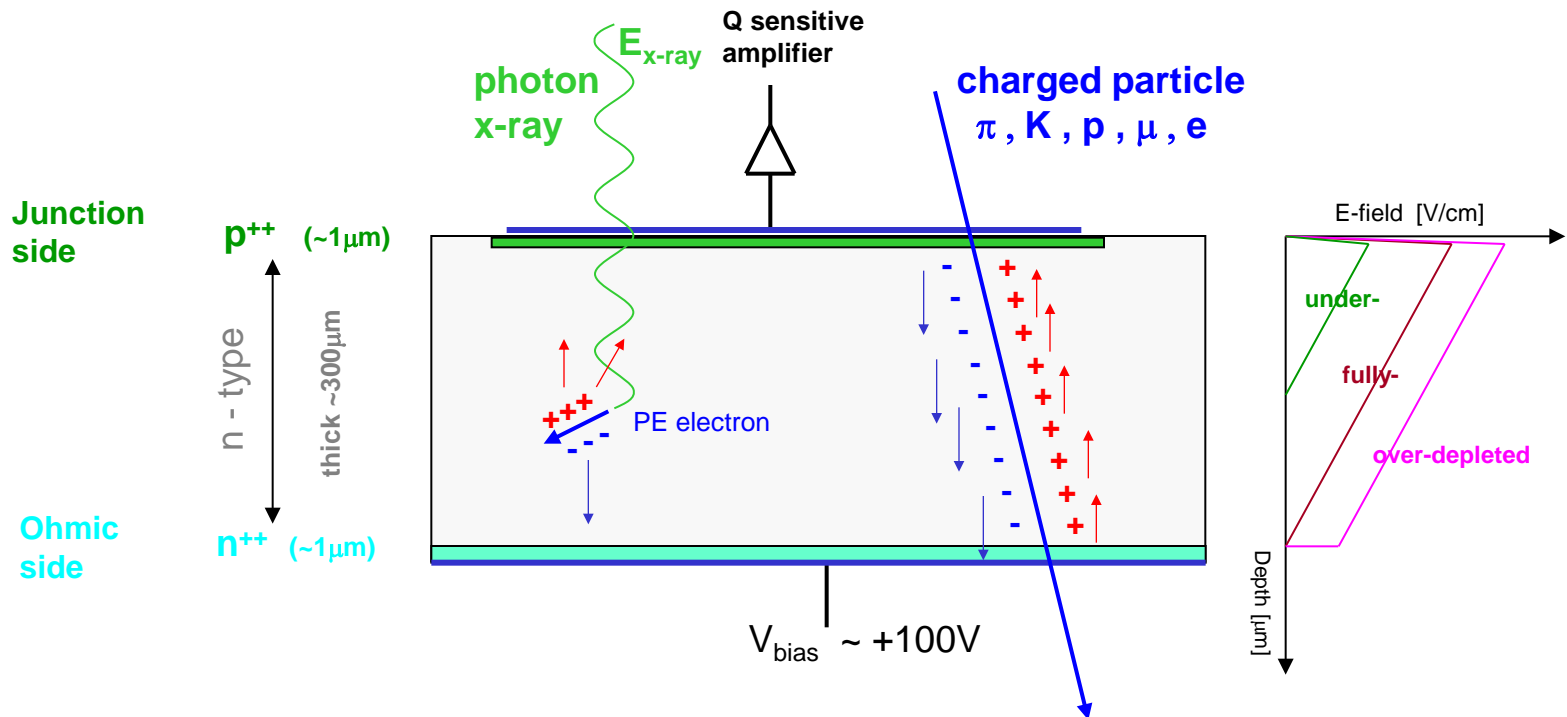
$$Q_{\text{leak}} = \text{Volume} / \rho \mu$$

Example : Silicon $\rho = 20 \text{ k}\Omega\text{cm}$ $d = 300\mu\text{m}$, Signal charge = $4f\text{Clb} = 24'000 \text{ e}$

Pad detector : $A = 1 \text{ cm}^2$ $Q_{\text{leak}} = 10^{-9} \text{ Clb}$ \rightarrow Poisson $\rightarrow \sigma \sim 80'000 \text{ e}$ \rightarrow **S/N ~ 0.3**

For Silicon sensors at room temperature need another trick !

Use of reverse biased diode as particle detector

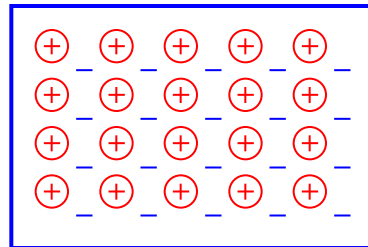
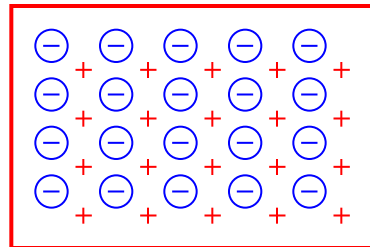


p-n-Uebergang und Raumladungszone

Feste Ladungen : \ominus \oplus
 Mobile Ladungen: $+$ $-$

p-typ

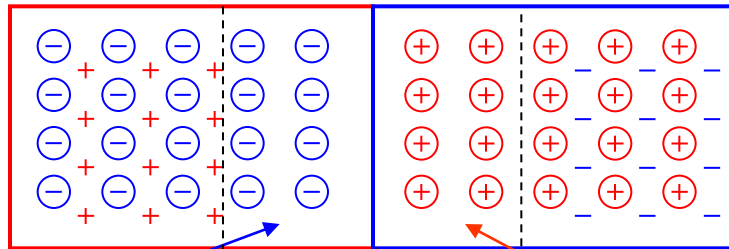
n-typ



p-n-Uebergang **vor**
 Ausgleich der Fermi-niveaus

Akzeptor
 Dichte N_A

Donator
 Dichte N_D



p-n-Uebergang **nach**
 Ausgleich der Fermi-niveaus

Negative
 Raumladungszone

Positive
 Raumladungszone

Ladungsneutralität \rightarrow

$$N_A \cdot x_A = N_D \cdot x_D$$

Spannungsabhängigkeit der p-n-Raumladungszone

Fest: \ominus \oplus
 Mobil: $-$ $+$

p-n-Diode:

C_{diode}

Spannung:

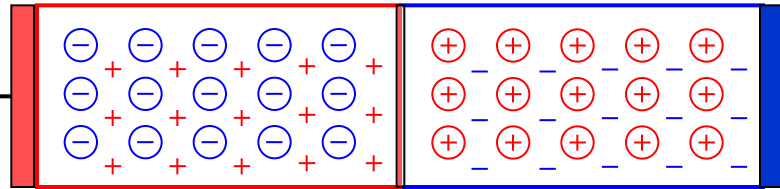
p-typ

n-typ

stark leitend

nicht definiert

$V_p \sim +1V$

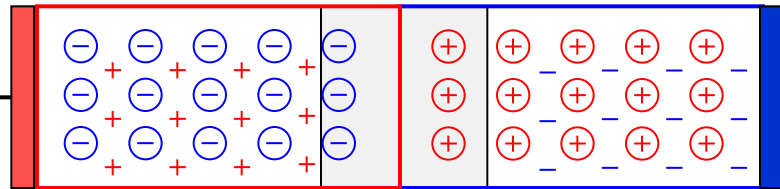


$V_n = 0V$

schwach leitend

gross

$V_p \sim +0.4V$

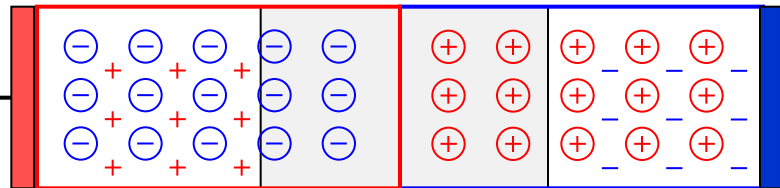


$V_n = 0V$

nicht leitend

nat.

$V_p = 0V$

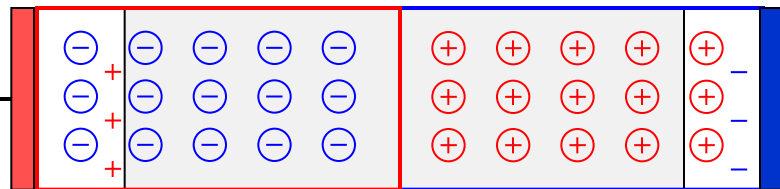


$V_n = 0V$

sperrend (Leckstrom)

klein (minimal)

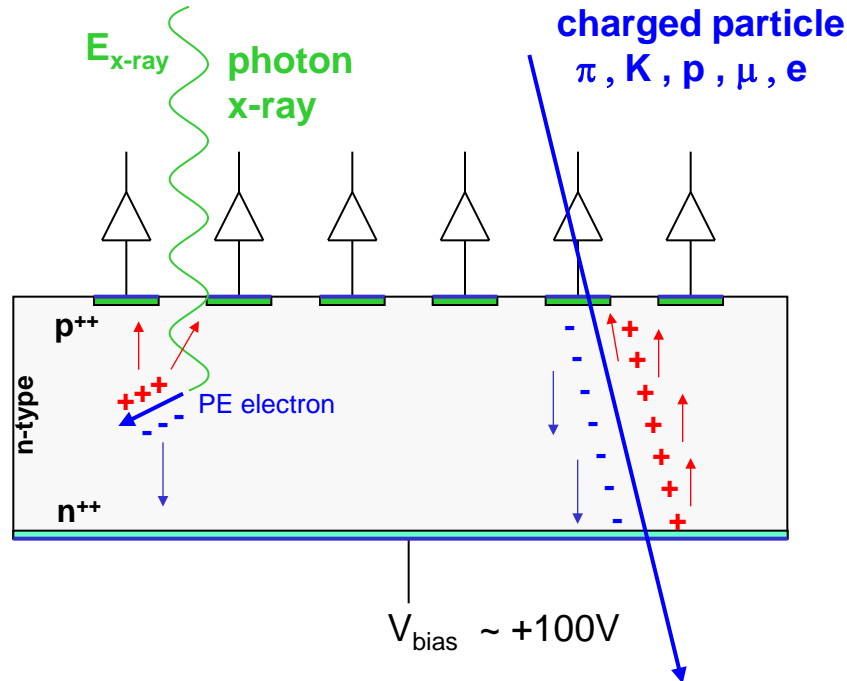
$V_p \sim -5V$



$V_n = 0V$

Raumladungszone (depletion layer)

Segmented Silicon Diode Sensors for Particle Detection



Shared Charge collection on segmented electrodes due to:

- Diffusion during drift time
- Lorentz angle due to presence of B-field
- Tilted tracks

Individual readout of charge signal on electrodes allows **position interpolation** that is better than pitch of segmentation.

carrier drift velocity $v = \mu E$

E = electric field [V/cm]

$\mu_e \sim 1200 \text{ cm}^2/\text{Vsec}$ mobility electrons

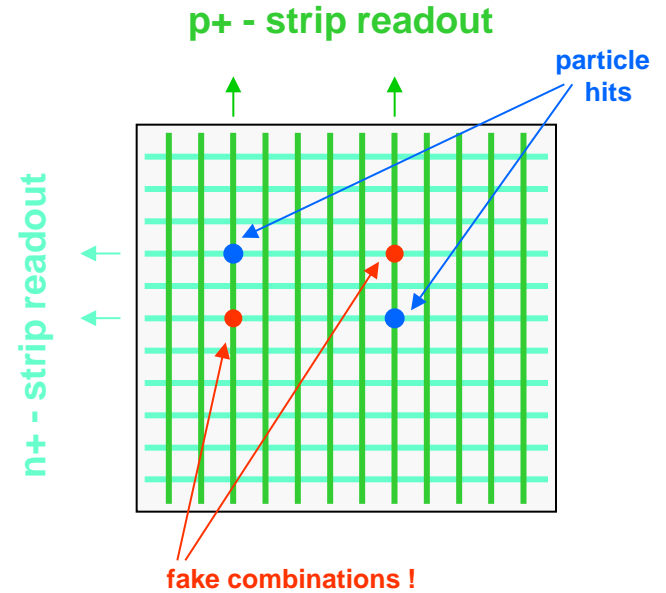
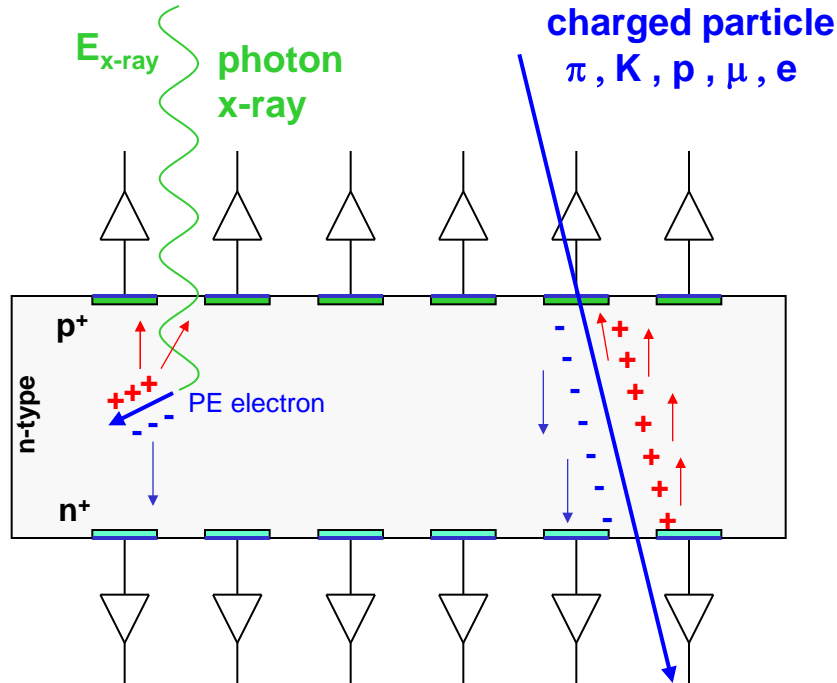
$\mu_h \sim 480 \text{ cm}^2/\text{Vsec}$ mobility holes

Charge diffusion $\sigma^2 = D t$

$D = \mu kT$ Fick-Einstein relation

Silicon microstrip detectors in HEP with pitch = $50\mu\text{m}$ have achieved in beam tests a position resolution of $\sim 1.3 \mu\text{m}$

Double Sided Silicon Strip Detectors

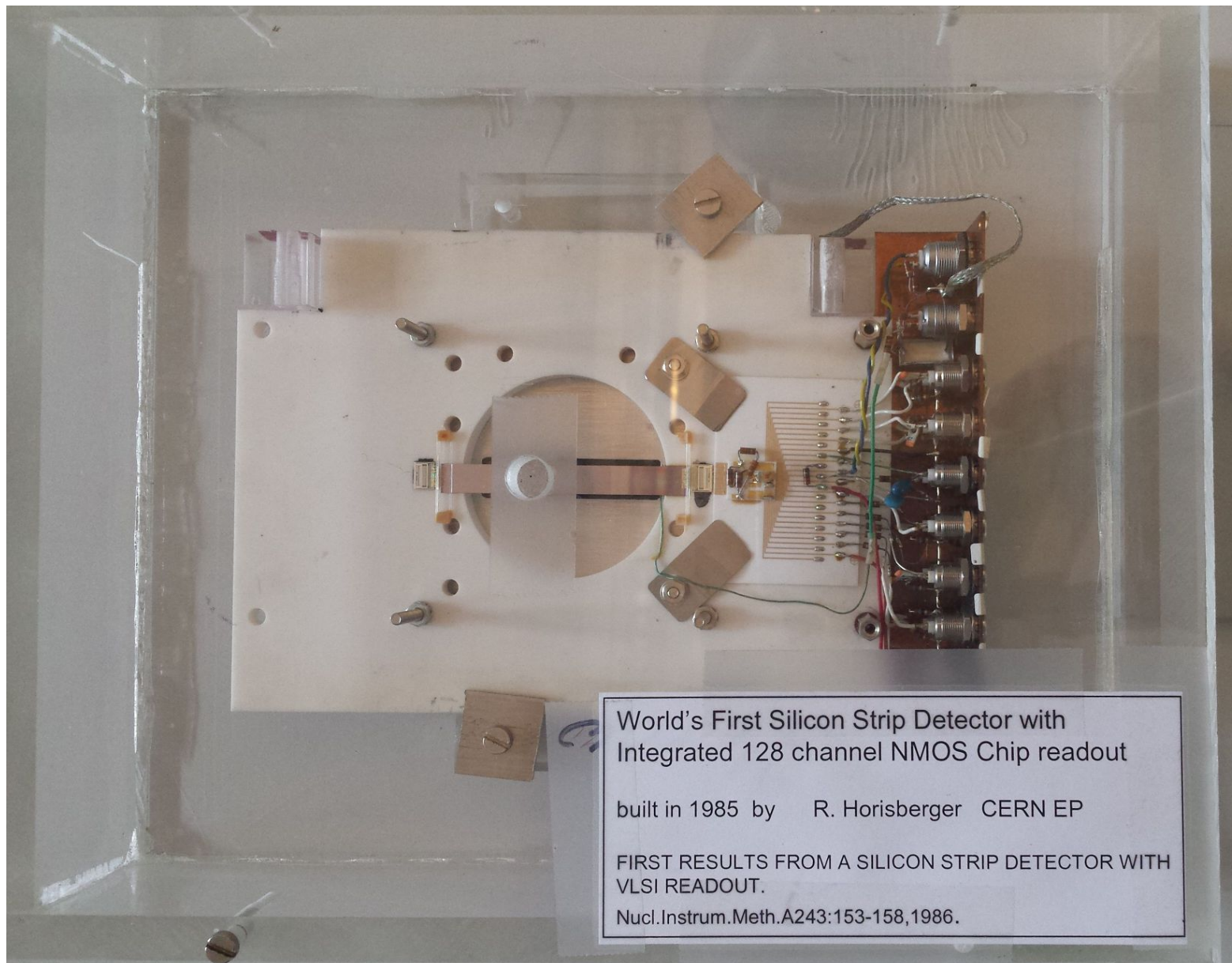


Crossed p-strip and n-strips allows readout of x & y coordinate of particle !

→ But **ambiguity problem** for many hits !

→ solved by **pixel segmentation**

First Silicon Strip Readout with ASIC



World's First Silicon Strip Detector with
Integrated 128 channel NMOS Chip readout

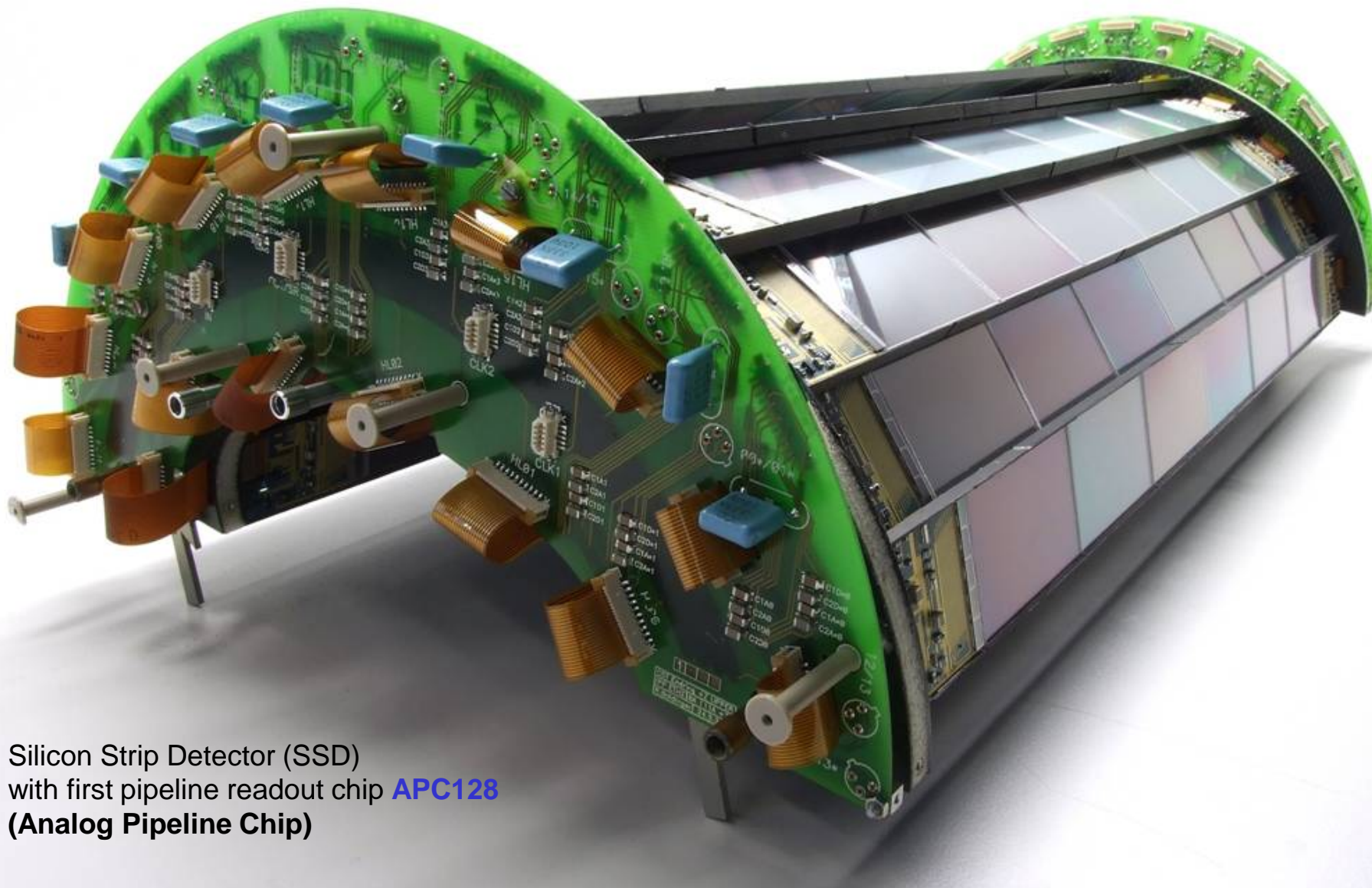
built in 1985 by R. Horisberger CERN EP

FIRST RESULTS FROM A SILICON STRIP DETECTOR WITH
VLSI READOUT.

Nucl.Instrum.Meth.A243:153-158,1986.

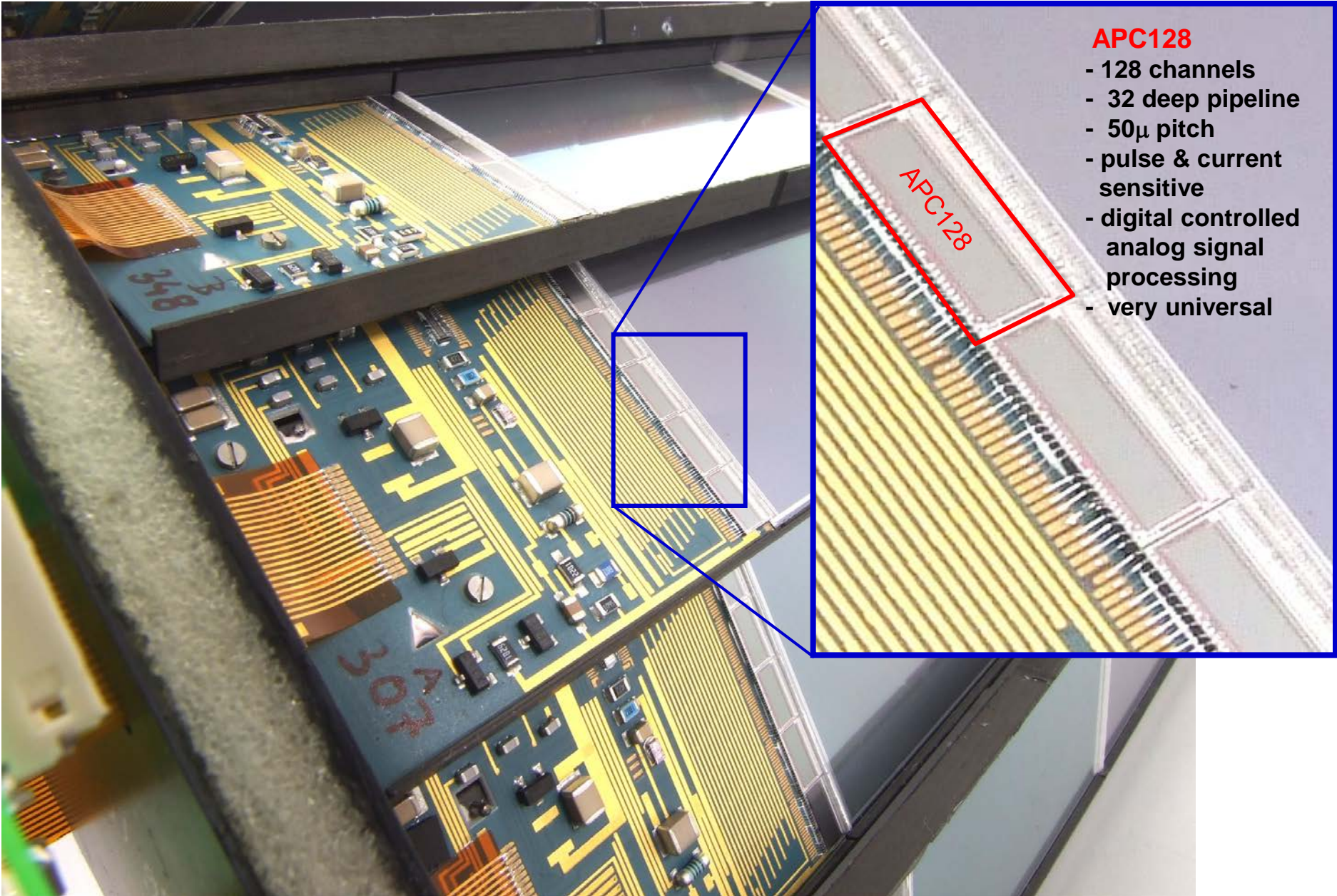
H1 Central Silicon Vertex Detector

Completely designed and built at PSI (1992-1996)



Silicon Strip Detector (SSD)
with first pipeline readout chip **APC128**
(Analog Pipeline Chip)

Analog Pipeline Chip for Si-Strips

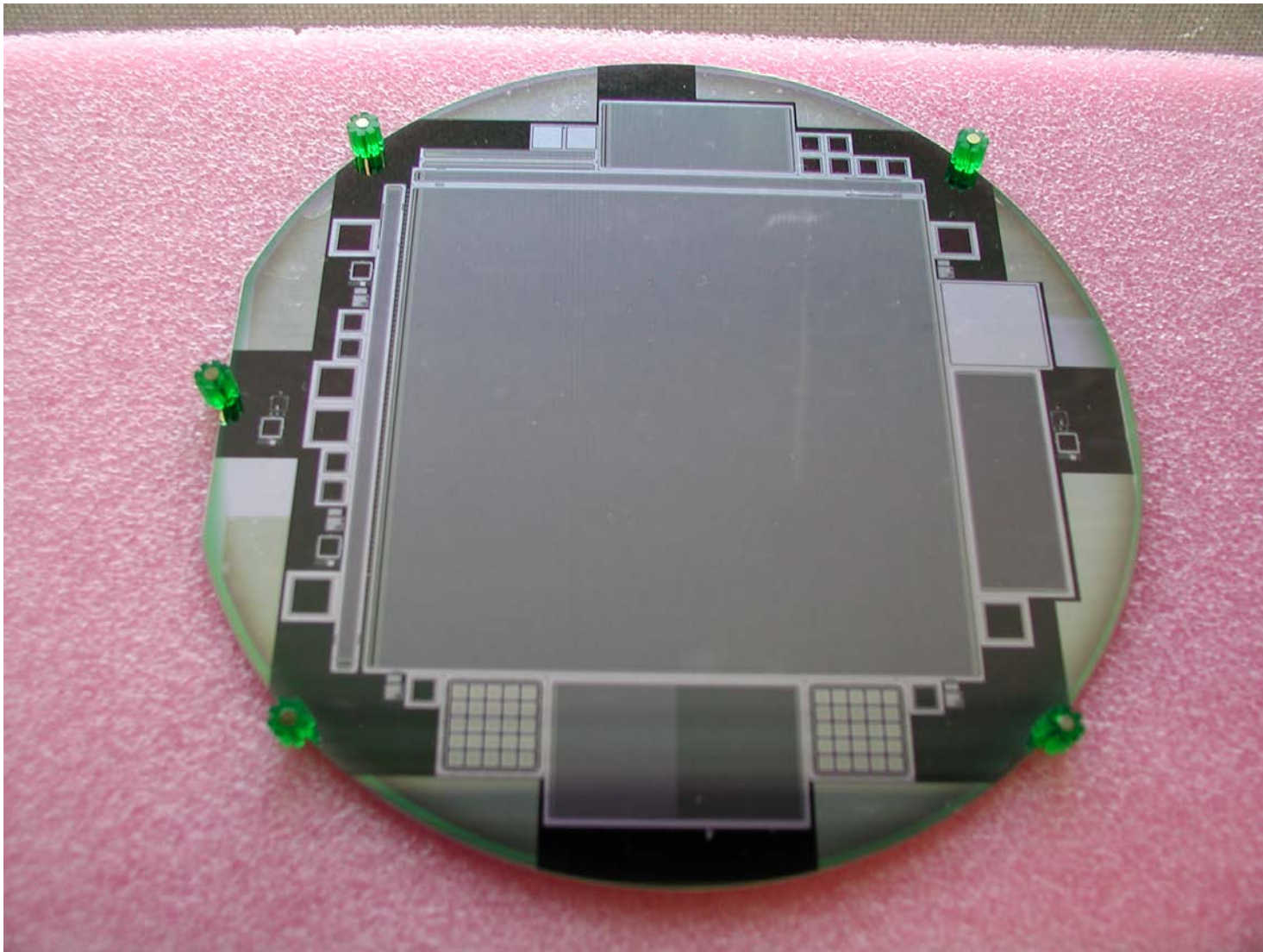


APC128

- 128 channels
- 32 deep pipeline
- 50 μ pitch
- pulse & current sensitive
- digital controlled analog signal processing
- very universal

Wafer eines Silizium Streifen Detektors

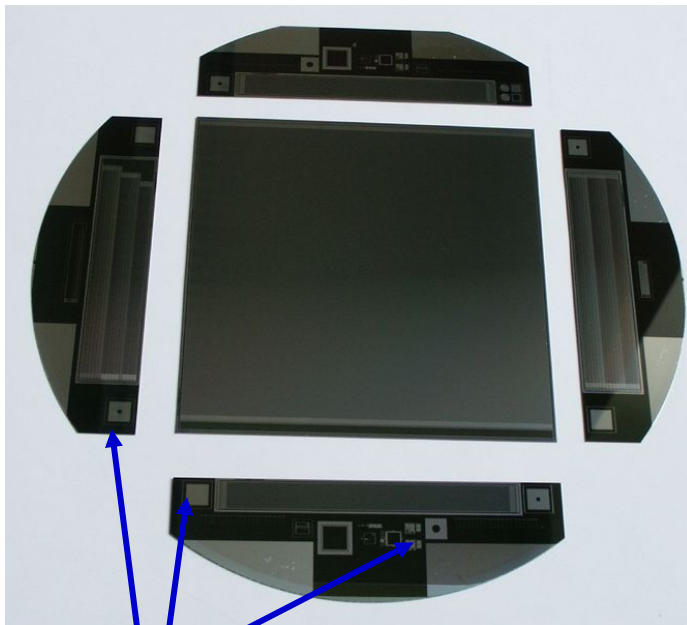
Typ. 6" ~ 150mm Durchmesser



Silizium Streifen Detektoren für Teilchenphysik Experimente

Wafer gesägt mit Diamant Säge

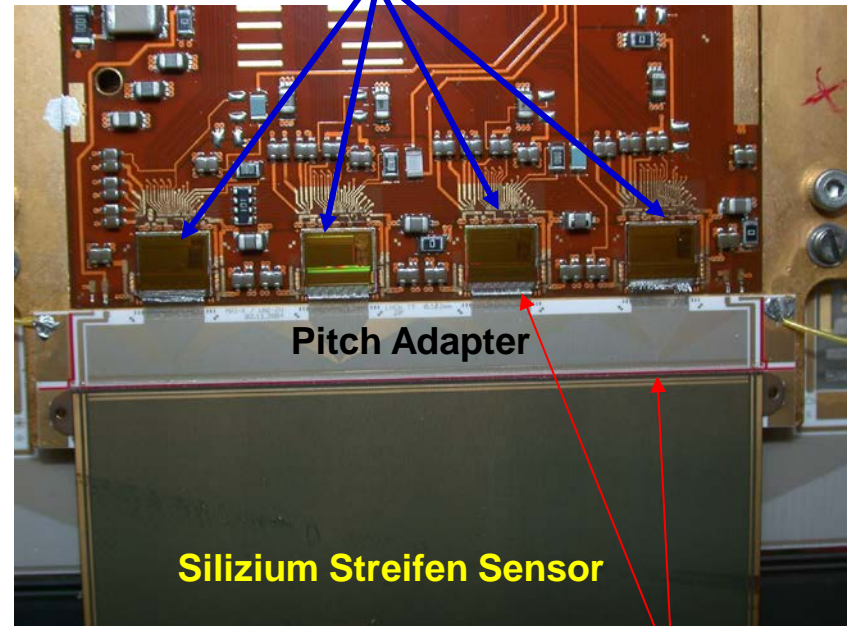
Z.B. 30 μ mBlatt Breite



Test-Strukturen zur Messung der Wafer Parameter
z.B. Implantationsdosis, Flächendioden,
Oxidkapazitäten, Poly-Si-Widerstände

Streifen Detektor mit CMOS Auslese-
elektronik auf Interconnect-Hybrid

CMOS Elektronik Chips (128
Kanäle / Chip) zur Auslese der
Signalladungen jedes Streifens



Ultraschall Draht-bonding
(typ. 25mm Al-Draht)

Silizium Streifen Detektoren für Teilchenphysik Experimente



TT-Station LHCb (Uni ZH)
(CMS Streifen Detektoren)



Vertex Locator (Velo) Detektor von LHCb
(Univ. Liverpool)

Benutzung von nicht orthogonalen Geometrien

Detektor mit Mini-Streifchen in Polar-Koordinaten

Silicon Strip Tracker

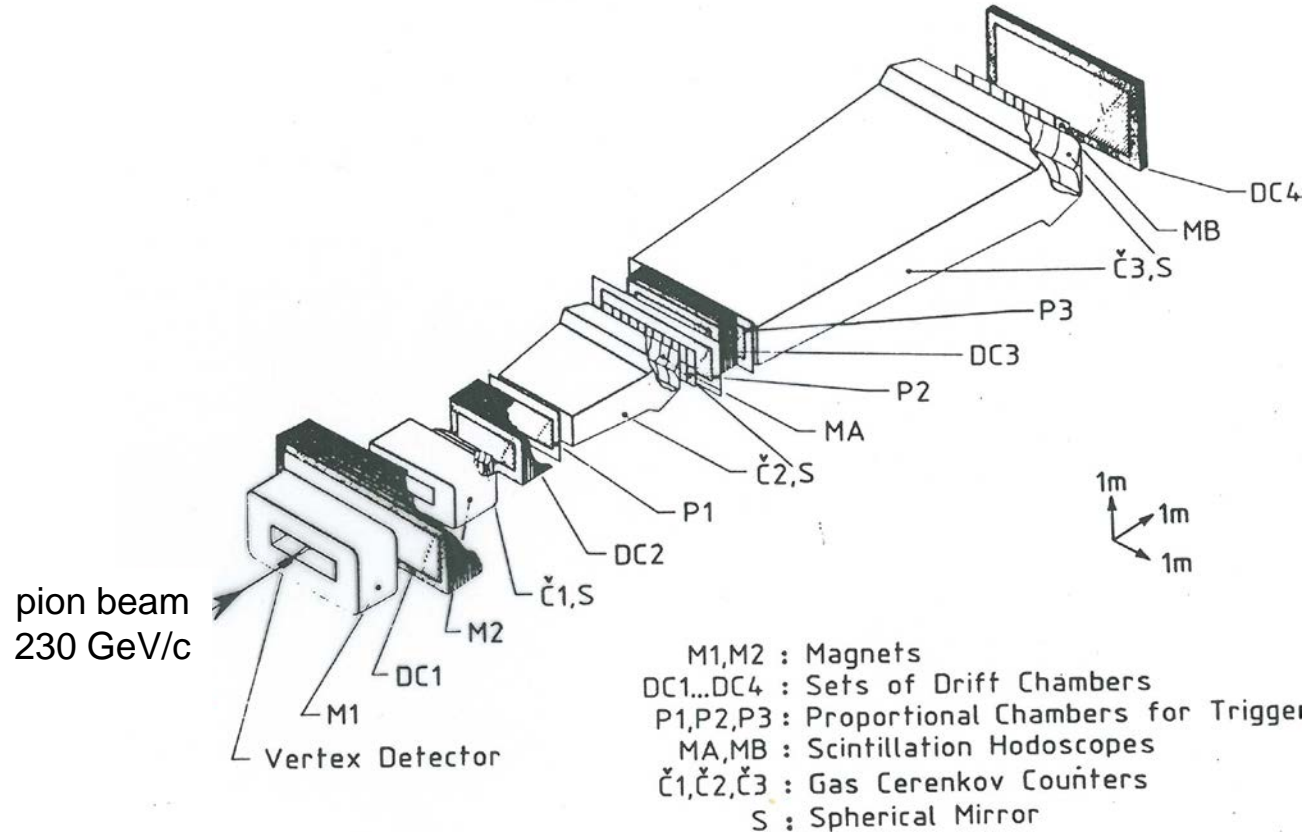
~ 12 Million
Readout Channel



TIB, TOB, TID & TEC build by European and US Groups (ca. 400 physicists)

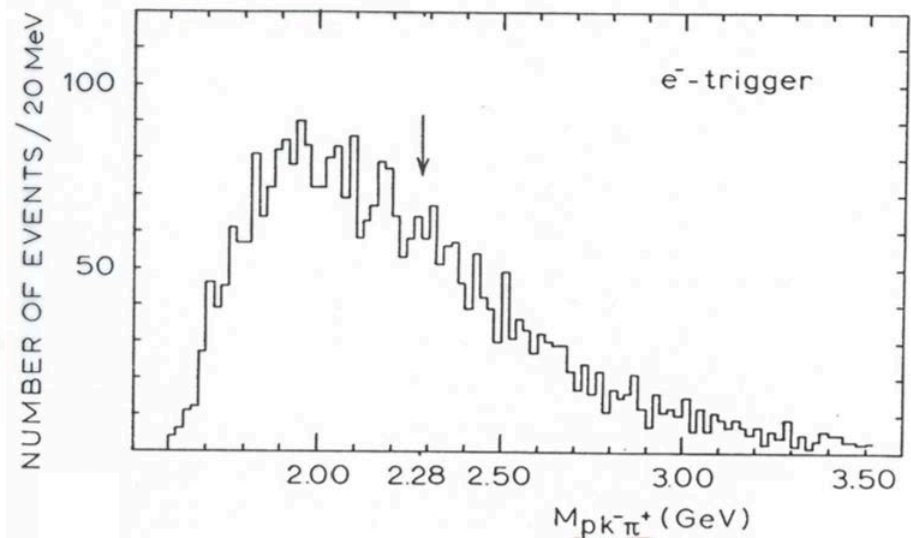
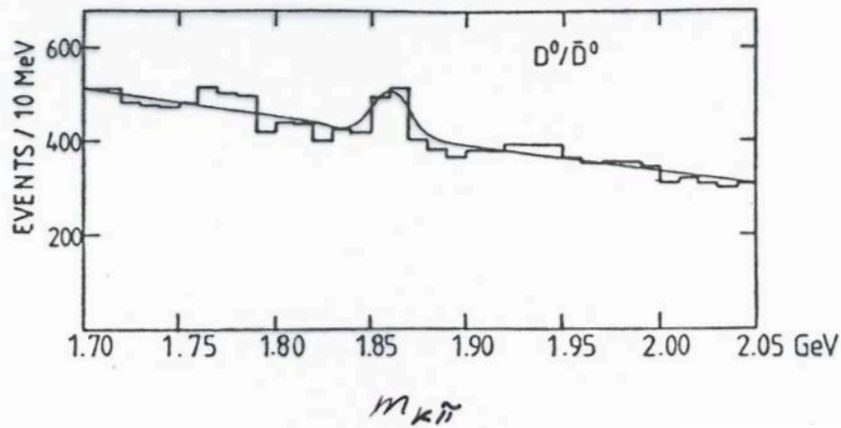
NA11 experiment searches hadronic charm

experimental observation of hadronic produced charm particle is rather difficult



NA11 experiment is rather complex and quite a big effort in hardware and people

experimental reconstruction of hadronic produced charm particle is not easy



experimental observation of easier channels worked, but seldom produced charm particles and lower branching ratio decays were not possible.

→ overwhelming, high rate hadronic background processes

→ selection of charm events by very precise lifetime tagging should help !

→ improve experiment by adding novel, very precise silicon vertex detectors

Silicon detectors boost NA32 experiment

Several groups of ACCMOR collaboration develop novel silicon detector technologies

NA11/32 becomes breeding ground of today's silicon precision vertex detectors

Silicon micro strip detectors in NA32

$\Lambda_c \rightarrow p K^- \pi^+$

with Si-strip detectors

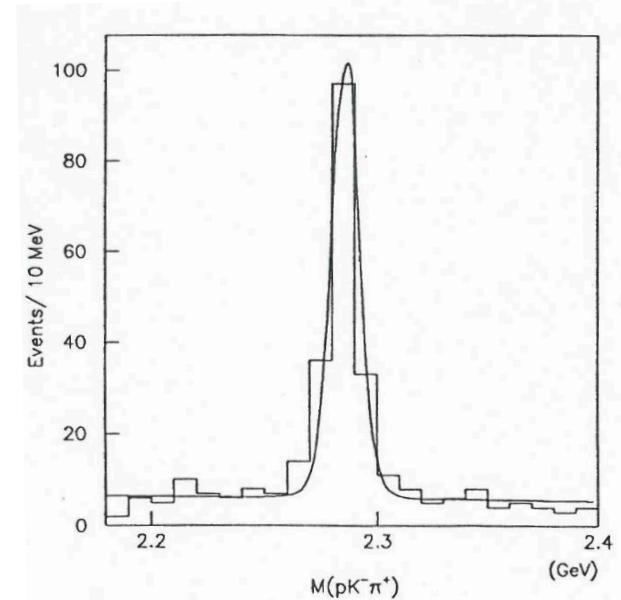
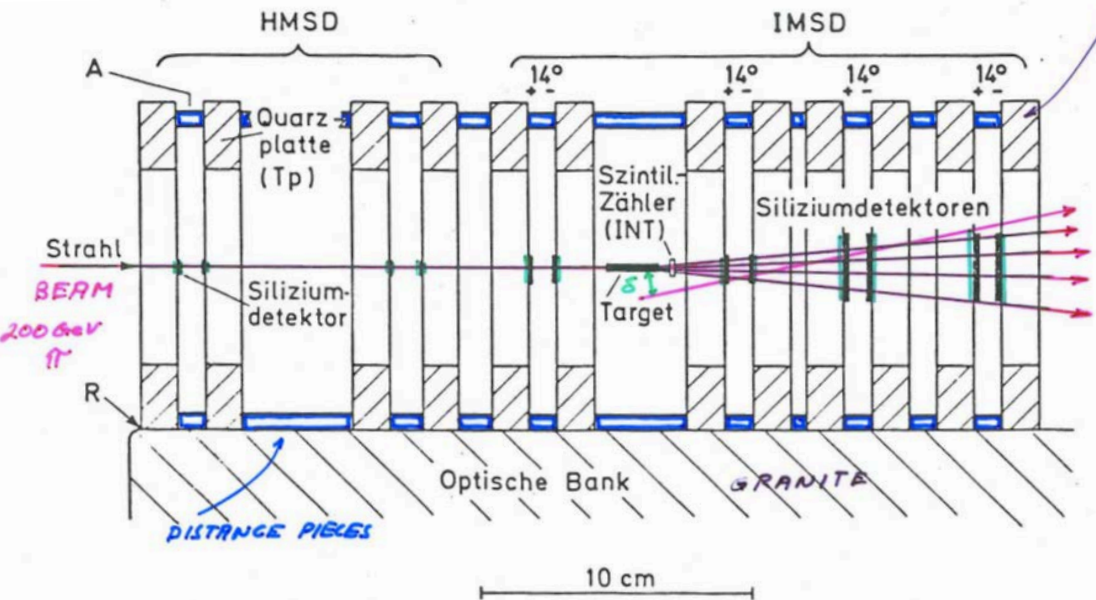


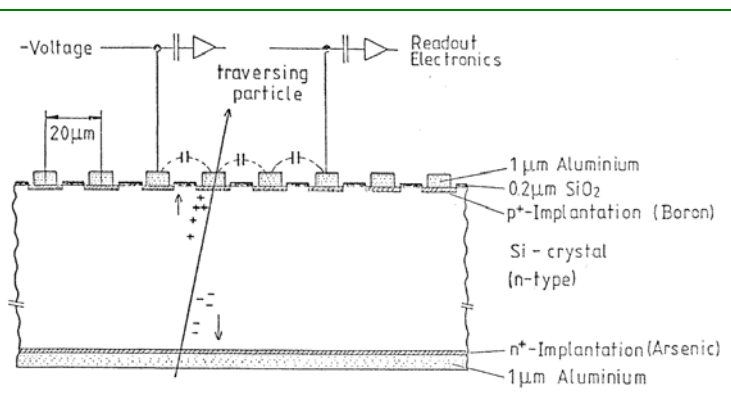
Fig. 1. $pK^- \pi^+$ invariant mass spectrum.

The addition of silicon micro strip detectors made a huge difference !

Small group pioneered and developed silicon micro strip detectors for NA32

A wealth of innovation:

- analog pulse height readout
- precision by interpolation
- capacitive charge division
- AC-coupled low noise electronics
- system & integration



Strip detector:

20μ strip pitch

60μ readout pitch →

4.5μ

120μ readout pitch →

7.9μ

resolution

Nuclear Instruments and Methods 205 (1983) 99–105.
North-Holland Publishing Company

99

A SILICON COUNTER TELESCOPE TO STUDY SHORT-LIVED PARTICLES IN HIGH-ENERGY HADRONIC INTERACTIONS

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CERN, Geneva, Switzerland

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Max-Planck-Institut für Physik und Astrophysik, Werner-Heisenberg-Institut, Munich, Fed. Rep. Germany

J. KEMMER
Technische Universität, Munich, Fed. Rep. Germany

Received 5 July 1982

A telescope consisting of six silicon microstrip detectors achieving 5 μm spatial resolution for minimum ionizing particles has been built. The design and fabrication of the counters, electronics, and mechanical set-up is described, and first results of its performance in a 175 GeV/c beam are reported.

1. Introduction

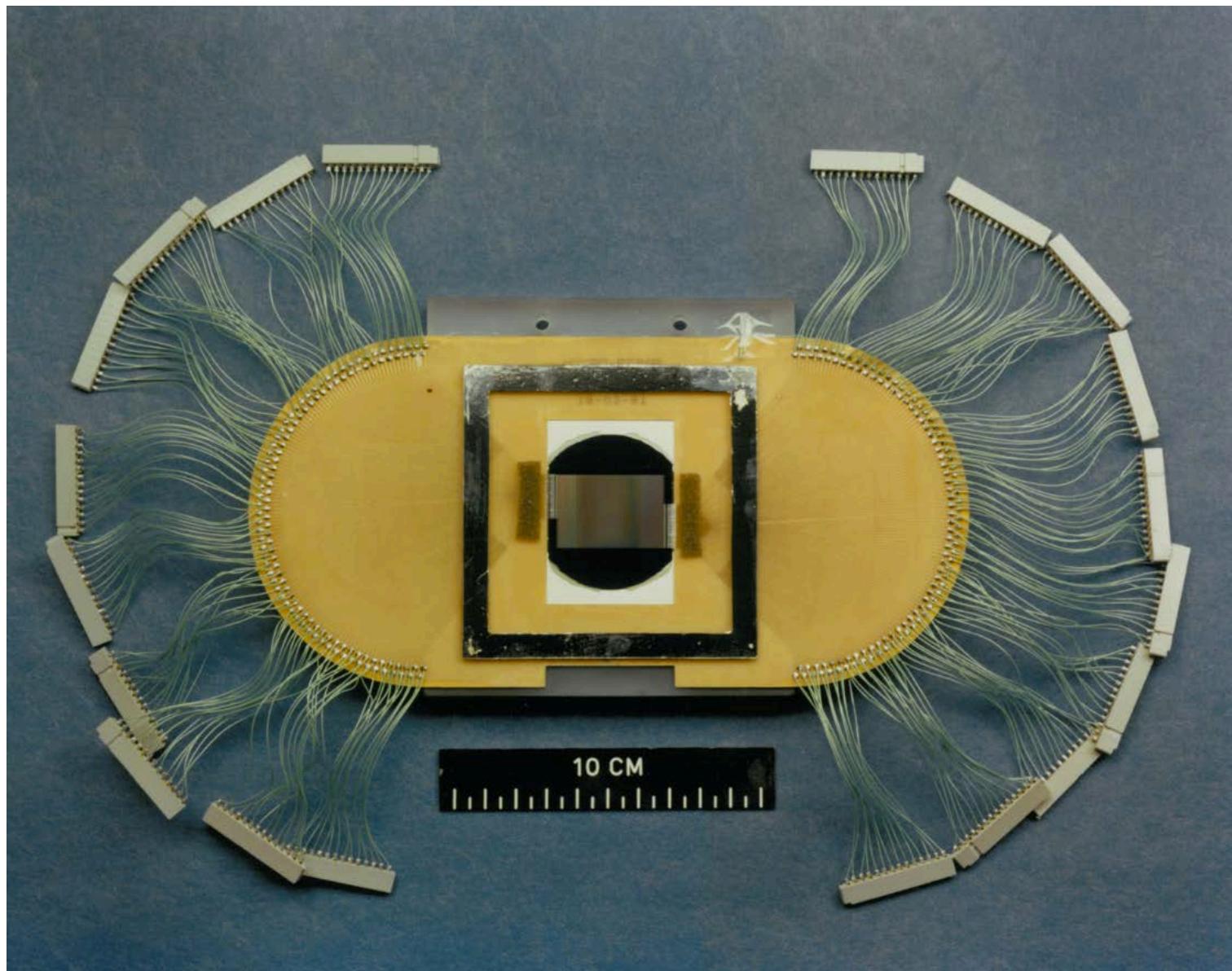
The telescope described in this article has been built for an experiment to study the production and properties of charmed particles in 100–200 GeV hadronic interactions in a beryllium target at the CERN Super Proton Synchrotron (SPS) **. The lifetime of charmed particles of a few times 10^{-13} s, their production cross-sections of a few microbarns, and the general features of hadronic interactions in this energy range, such as the charged multiplicity of ~ 10 and the concentration of most of the particles in a narrow forward cone, have defined the required performance of the counters:
– spatial resolution of ≤ 10 μm;

2. The silicon microstrip detectors

2.1. Principles of operation

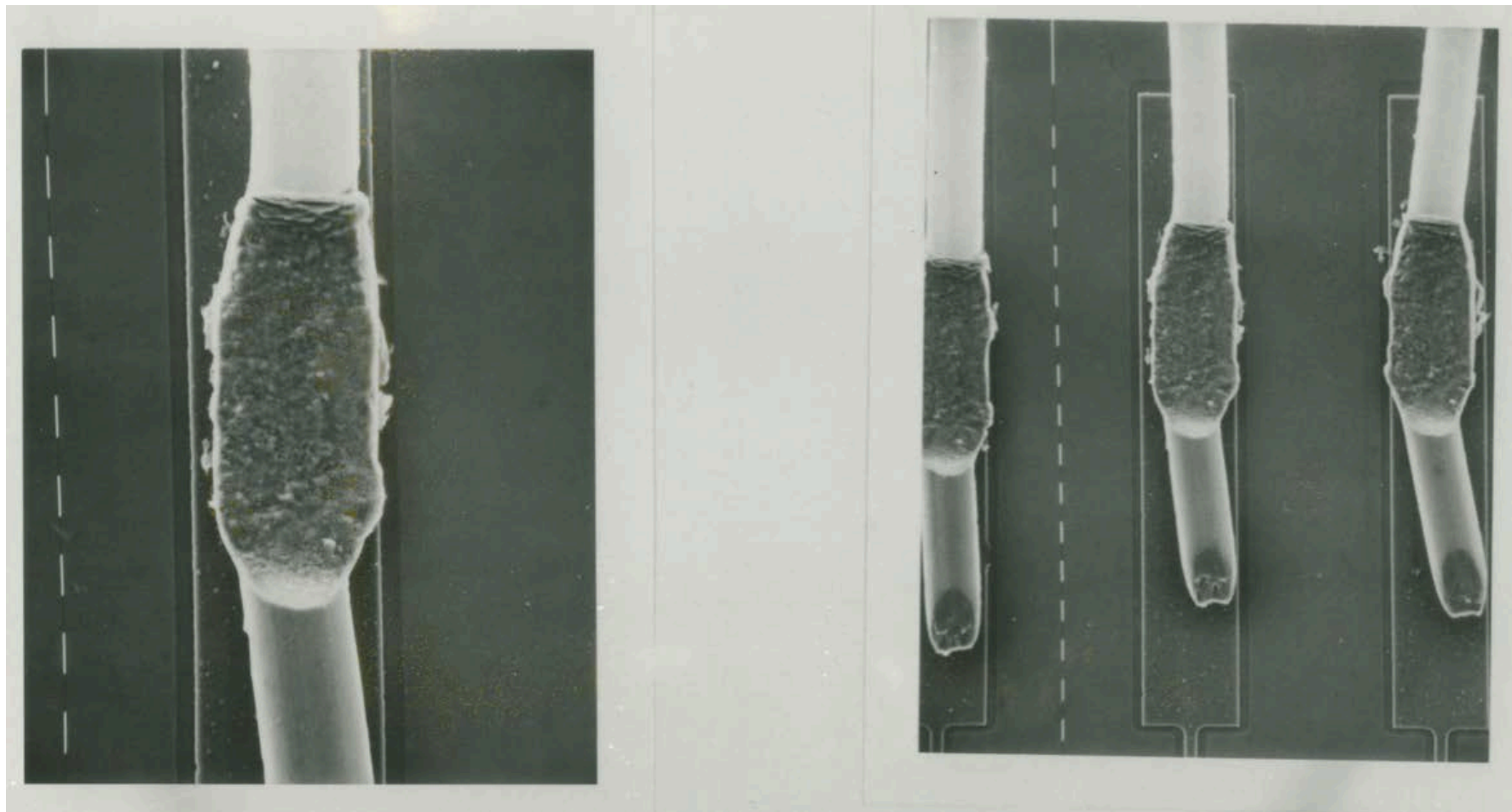
Fig. 1 shows schematically a cross-section of the detector. The basic material is a high-ohmic (~ 2 kΩ·cm) n-doped silicon crystal, 2 inches in diameter and 280 μm thick. One face of the crystal is aluminized. On the other face, the sensitive area of the counter (a rectangle of 24 mm × 36 mm in our case) is covered with p⁺ implanted diode strips (1200 strips of 12 μm × 36 mm and 20 μm pitch) and Al contacts. Connecting the strips to a negative voltage of 160 V depletes the n-doped silicon crystal of free charge carriers, leaving

Silicon strip detectors developed for NA32



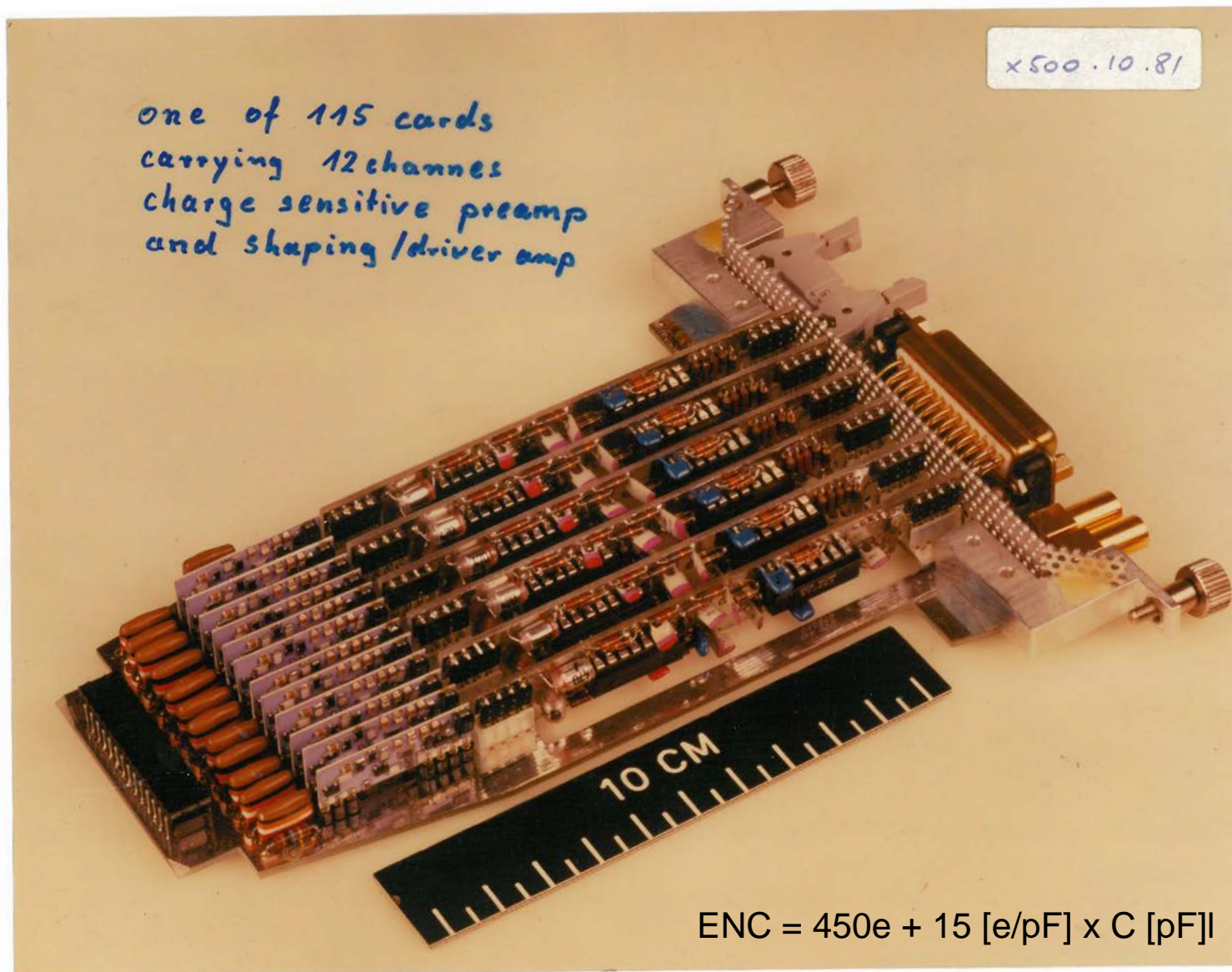
Silicon strip detectors developed for NA32

In HEP ultrasonic wire bonding was at the time pretty exotic !



Silicon strip detectors developed for NA32

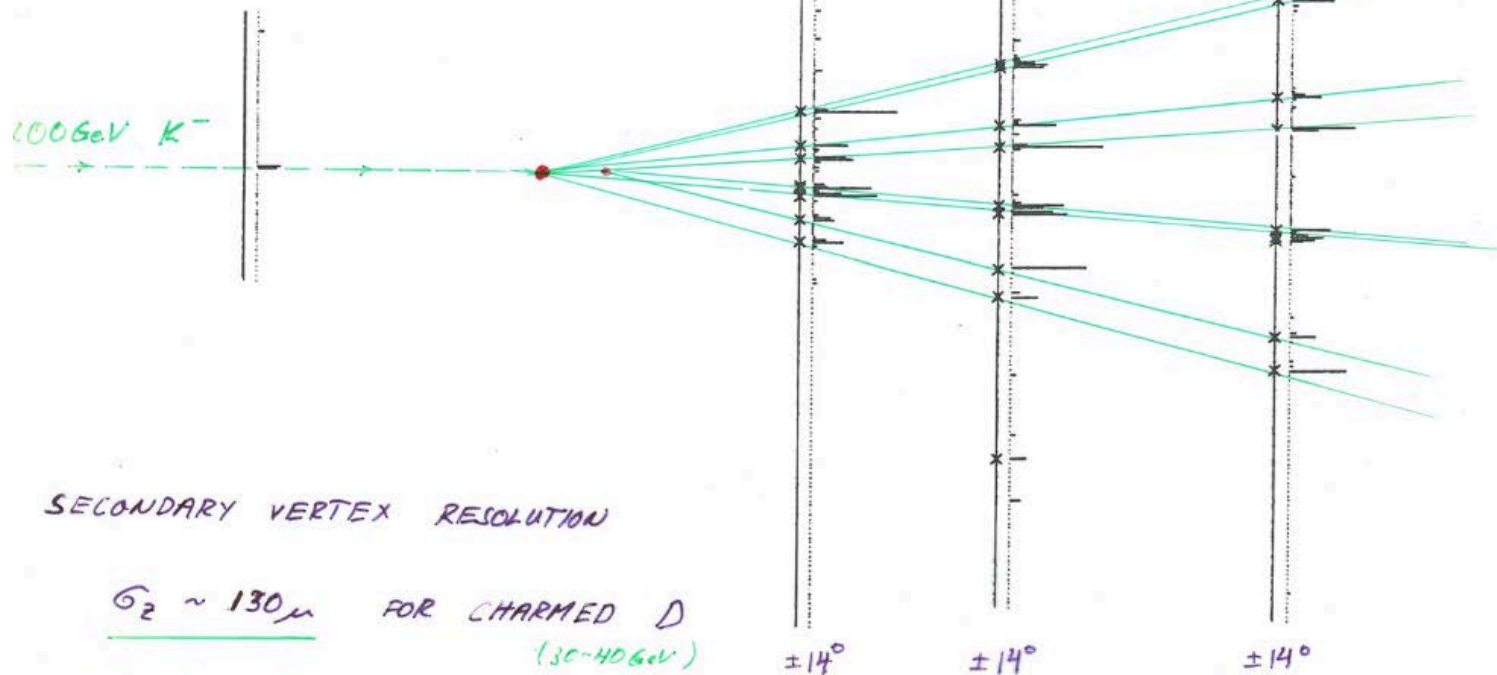
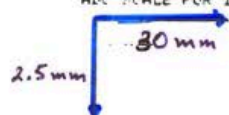
cost per electronic channel was the limit for larger applications (~100-200 CHF/channel)



Secondary charm vertices with NA32

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DISPLAY FILE CREATED DAY 850520 TIME 1954
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PEW LPLBEA = 2 IPLINT = ** NSUM1 = *** NSUM2 = **** ESOP FLAGS = *****
SIM LPLBEA = 2 IPLINT = ** LSUM1 = *** LSUM2 = **** ESOP FLAGS = *****
CURRENT VIEW IS 3
UMSL TRACKS AND VERTICES DISPLAYED
X - SCALE 29.8760 Y - SCALE 2.5000
ADK SCALE FOR 1 MIN. I. PARTICLE
    
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SECONDARY VERTEX RESOLUTION

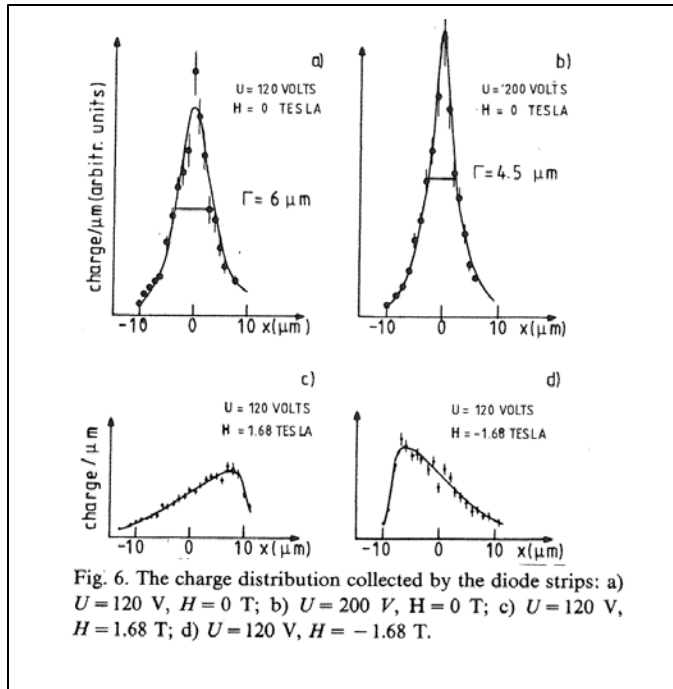
$\sigma_z \sim 130 \mu$ FOR CHARMED D
(30-40 GeV)

$\langle Z_{s,v} \rangle \sim 3-4 \text{ mm}$

$\sigma = 4.5 \mu, 7.9 \mu$ FOR 60 $\mu, 120 \mu$ READ OUT.

NA32

the “classical” paper on how to obtain the best resolution with charge interpolation



CHARGE COLLECTION IN SILICON STRIP DETECTORS

E. BELAU, R. KLANNER, J. LUTZ, E. NEUGEBAUER, H.J. SEEBRUNNER and A. WYLIE
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U. KÖTZ *
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M. RIEBESELL **
University of Hamburg, Fed. Rep. Germany

NIM 214 (1983) 253-260

The charge collection in silicon detectors has been studied, by measuring the response to high-energy particles of a $20 \mu\text{m}$ pitch strip detector as a function of applied voltage and magnetic field. The results are well described by a simple model. The model is used to predict the spatial resolution of silicon strip detectors and to propose a detector with optimized spatial resolution.

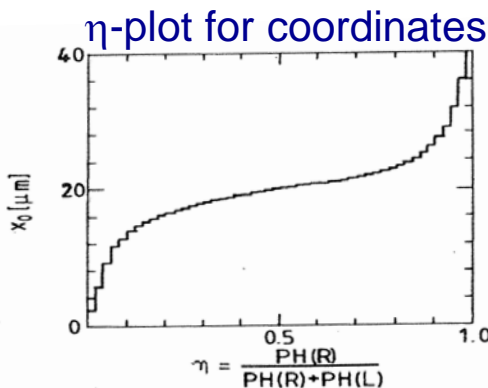
1. Introduction

Recently the planar process, developed for producing microelectronics, has been adapted to the fabrication of detectors for ionizing radiation [1]. One of the first applications of this new technology was the development of microstrip detectors with high spatial resolution as a vertex telescope for elementary-particle interactions [2]. In this work we describe a

2. The experimental apparatus

2.1. The microstrip detector

A high-ohmic ($\sim 3 \text{ k}\Omega \text{ cm}$) n-doped silicon crystal, oriented in the 1,1,1-direction, 2 inches in diameter and $280 \mu\text{m}$ thick, is used as base material. One face of the crystal is aluminized. On the other face the sensitive area of the counter ($2 \text{ mm} \times 32 \text{ mm}$) is covered with p^+

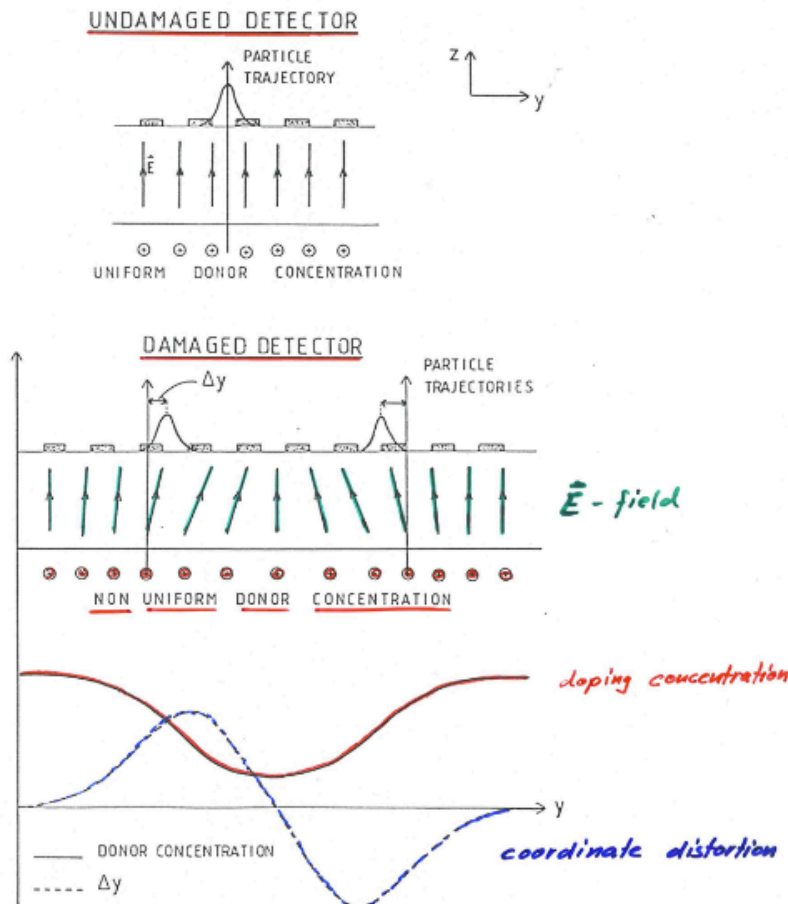


η -algorithm is now used everywhere in silicon detectors

test beam 1994: $25 \mu\text{m}$ strip readout \rightarrow $1.3 \mu\text{m}$ resolution
(P. Weilhammer et. al.) \rightarrow HE-LHC, FCC

Silicon detectors damaged by π beam

after running several years in the pion beam small coordinate shifts showed up.



RADIATION DAMAGE IN SILICON STRIP DETECTORS

H. Dietl¹⁾, T. Gooch¹⁾, R. Klanner²⁾, M. Pepé⁴⁾ and F. Wickens⁴⁾

The high resolution silicon strip detectors of the ACCMOR collaboration [1] have been used during 1982-1984 to measure production and decay of charm particles in hadronic interactions. During this time, they have been exposed to $2.5 \cdot 10^{12}$ hadrons, focussed onto a spot of $\Gamma_x \times \Gamma_y = 12 \text{ mm} \times 0.5 \text{ mm}$. The following effects have been observed [2]:

- (i) an increase in leakage current approximately proportional to the number of particles traversing a detector element $I_{\text{leak}} = I_0 + \alpha \cdot N \cdot d$ ($\alpha = 1.3 \cdot 10^{-8}$ nAmp/cm, N . . . number of particles traversing the detector element of thickness d , I_0 . . . leakage current without radiation damage)
- (ii) a voltage current characteristic, deviating from the $V^{1/2}$ -dependence of an undamaged detector (Fig. 1). This is interpreted as a result of an increased bulk resistivity due to radiation damage
- (iii) a systematic shift of the measured coordinate (Fig. 2) of up to $10 \mu\text{m}$. It can be explained by the transverse electric field inside the silicon crystal due to the change in resistivity from radiation damage. It is found that 0.05 doping centres are removed per one cm path of a minimum ionizing particle in the crystal.

References

- [1] B. Hyams et al., NIM **205** (1983) 99;
E. Belau et al., NIM **214** (1983) 255.
- [2] H. Dietl et al., Radiation Damage in Silicon Strip Detectors, paper submitted to this conference.

Figure Captions

Fig. 1 Current voltage characteristics for detector elements with strong (#25) and little (#8) radiation damage.

Fig. 2 Systematic shift in measured coordinate as function of position. The beam, which caused the radiation damage, was centred at 0 with a full width of $400 \mu\text{m}$.

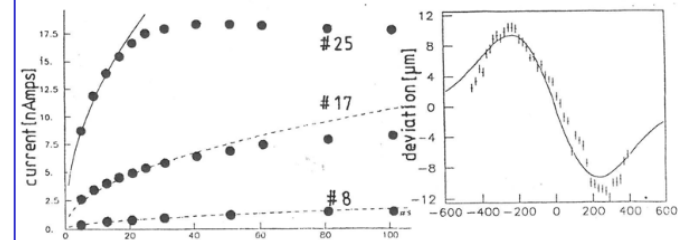


Fig. 1 voltage [Volts]

Fig. 2 position [μm]

- 1) Bristol University, Bristol, U.K.
- 2) DESY, Hamburg, Fed. Rep. Germany
- 3) Max Planck Institut für Physik, Munich, Fed. Rep. Germany
- 4) Rutherford Appleton Laboratory, Chilton, Didcot, U.K.

Bari 1985

first observation of doping change \rightarrow type inversion

Radiation Damage to Silicon sensors

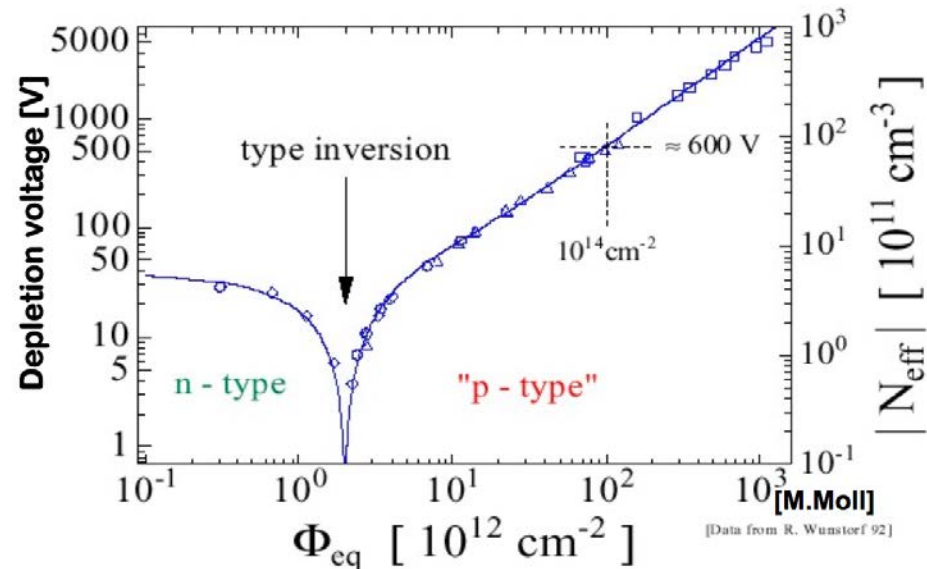
(basic material properties studies by RD50)

Irradiation in silicon sensors gives :

- Surface damage from Ionizing Energy Loss (IEL) → surface charges (SiO_2)
- Crystal damage from Non-Ionizing Energy Loss (NIEL) → energy levels in bandgap the latter leading to leakage current, trapping centers and doping effects.

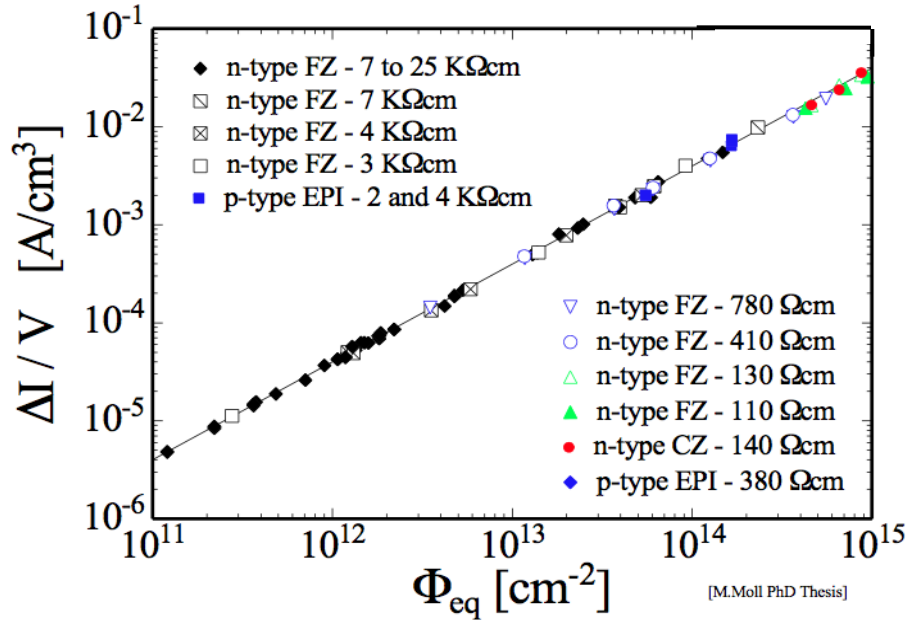
→ Type Inversion (doping)

Normalize dose Φ_{eq} to damage of 1-MeV-neutrons

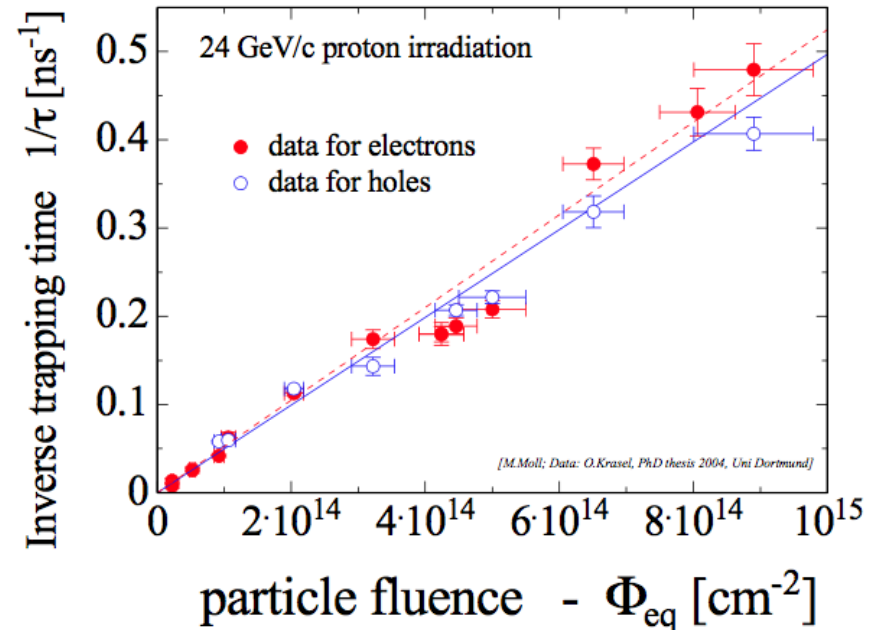


Observe the generation of universal, device doping independent

leakage currents



charge trapping times

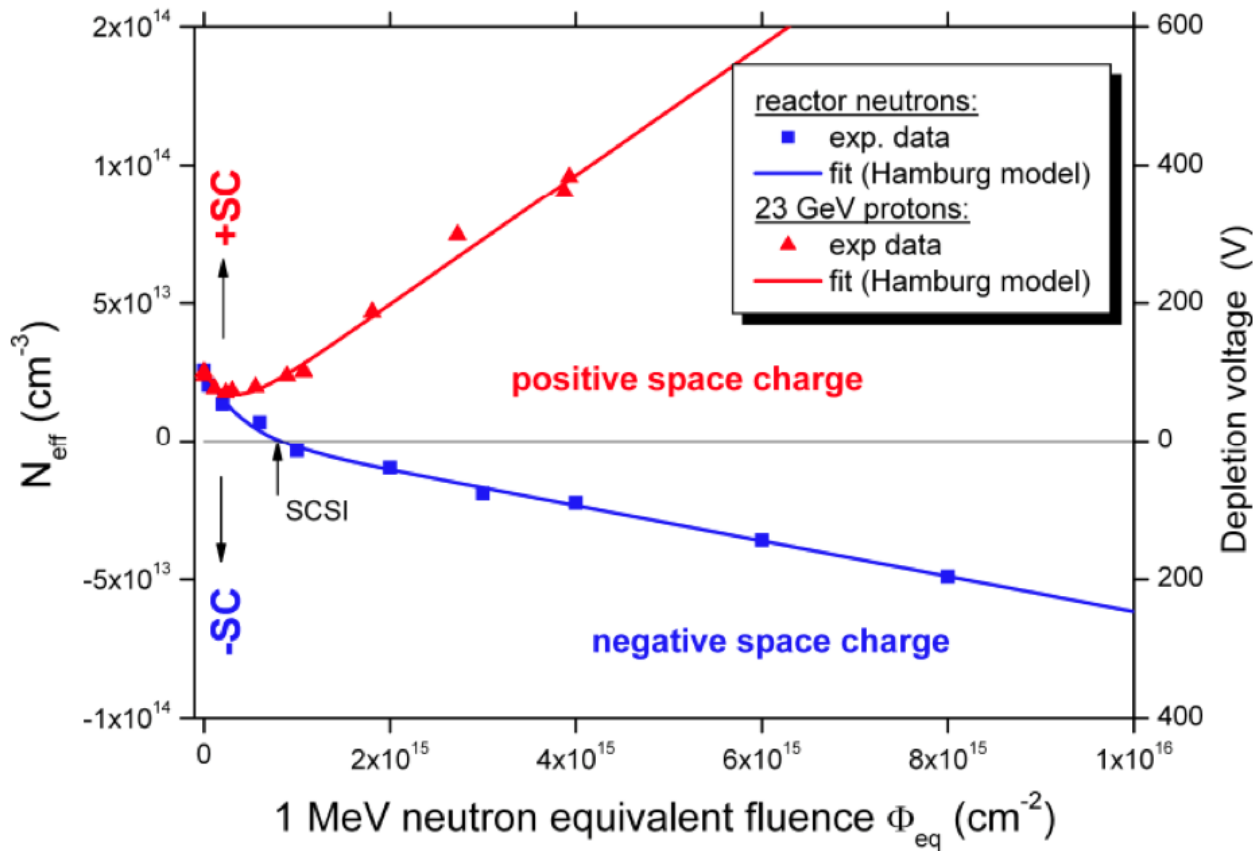


Signal charge trapping is **dominant** effect of irradiation at $10^{15} n_{eq}$ and above !

$\tau_{eff}(10^{15} n_{eq}) = 2 ns$	$w = v_{sat} \tau_{eff} = 200 \mu m$
$\tau_{eff}(10^{16} n_{eq}) = 0.2 ns$	$w = v_{sat} \tau_{eff} = 20 \mu m$

charge collection distance

Effective doping concentration N_{eff} depends on radiation activated defects:



Epitaxial silicon diodes irradiated with:

23 GeV protons

reactor neutrons

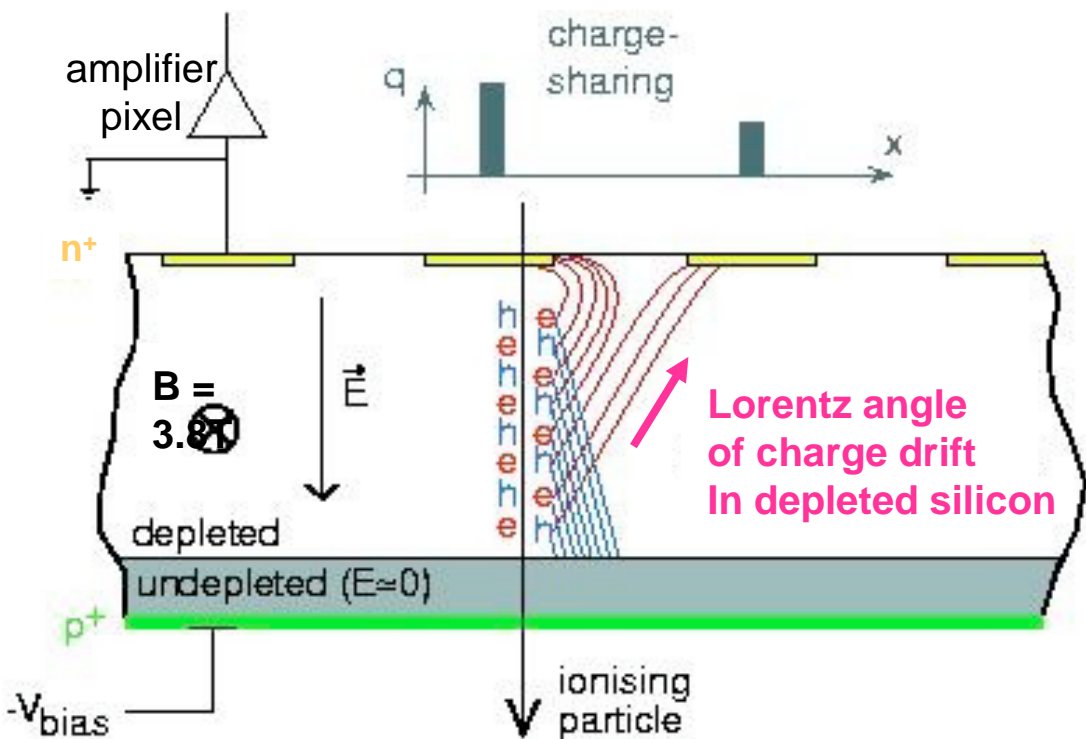
Depending on radii, HL-LHC experiments will expose their silicon sensors more to charged hadrons or neutrons → pixels (more hadrons) & strips (more neutrons)

Pixel Sensor: Precision by Sharing

Charge sharing of collected signal charge

→ **precision coordinates** $\sim 10\text{-}20\mu$

in both directions $r\text{-}\phi$ & z

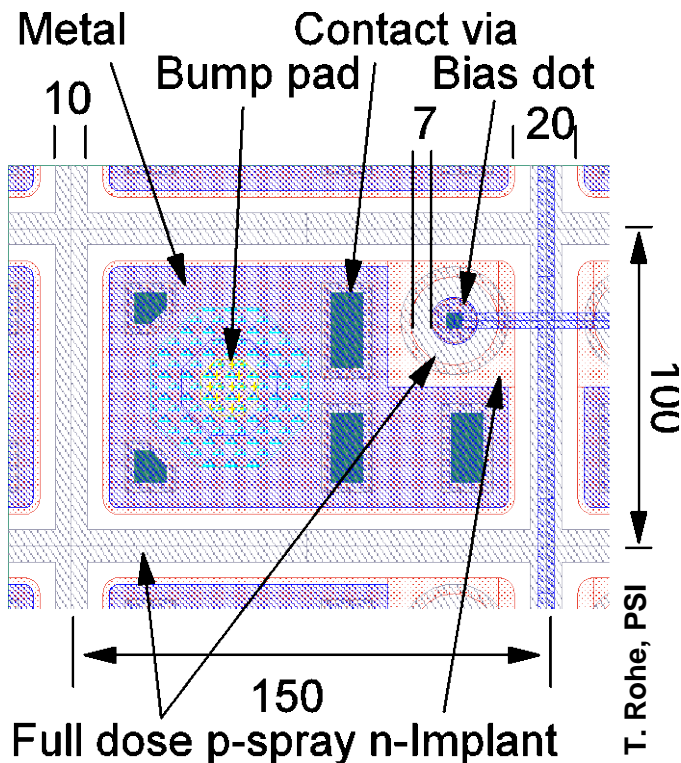


Sensor for LHC conditions

- work after large π -fluences
- n^+ -pixel on n -silicon design
- silicon type inversion $n \rightarrow "p"$
- good signal at LHC fluences
- graceful degradation
- resolution by charge sharing
- track angle dependence
- Lorentz angle dependence
- low pixel capacitance
- robust HV behavior

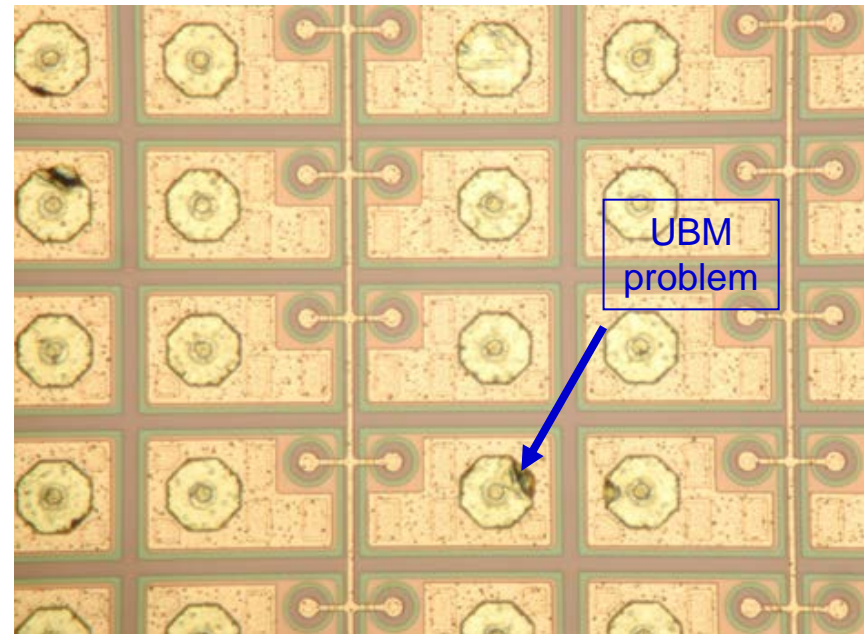
Design of sensor masks at PSI

- optimize position resolution $\sim 10\text{-}15\mu$
- minimize pixel capacitance $\sim 80\text{fF}$
- optimize HV robustness $\sim 600\text{V}$



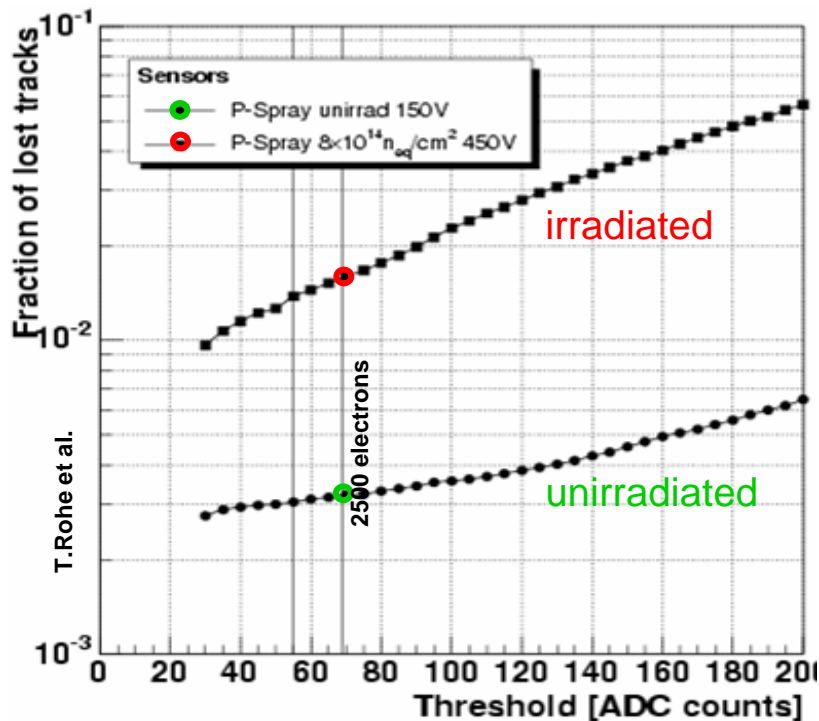
Final Choices:

- n⁺-on-n - Silicon (285 μm thick)
- Size: 150 μm \times 100 μm



Si-Sensor - ROC systems detect MIP particles at fluence well up to $5 \times 10^{15} / \text{cm}^2$ → **SLHC**

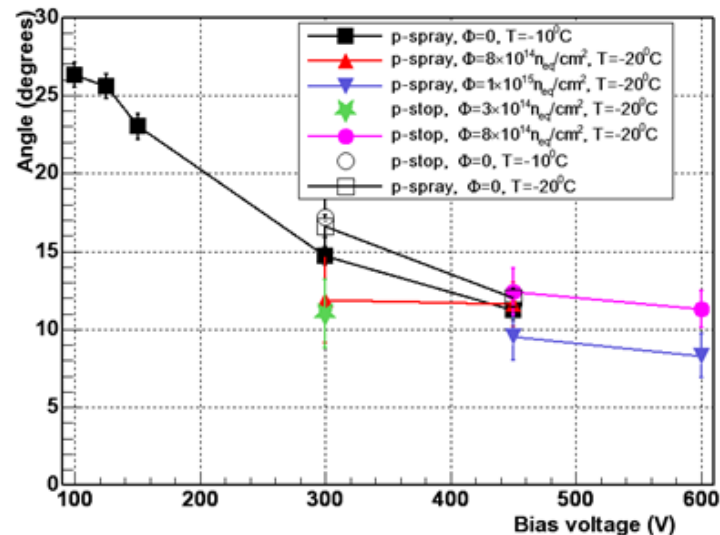
Signal charge after $8 \times 10^{14} \text{ cm}^{-2}$



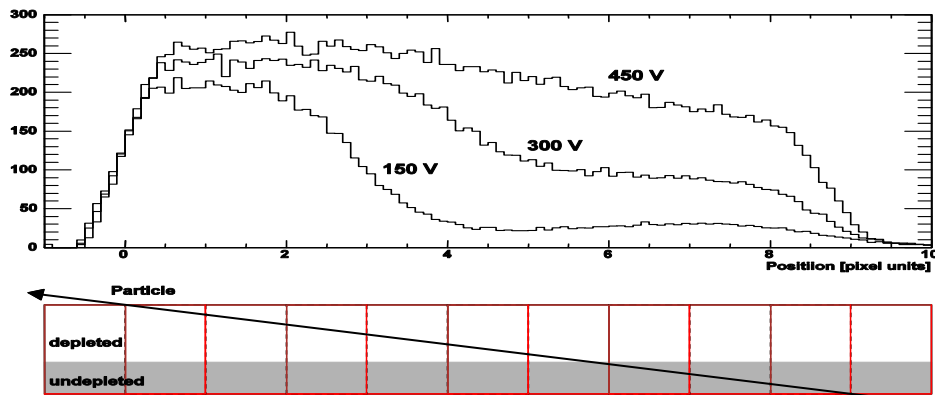
After many irradiations and beams tests at CERN :

→ Sensors are fit for LHC !

Lorentz angle at B=4Tesla

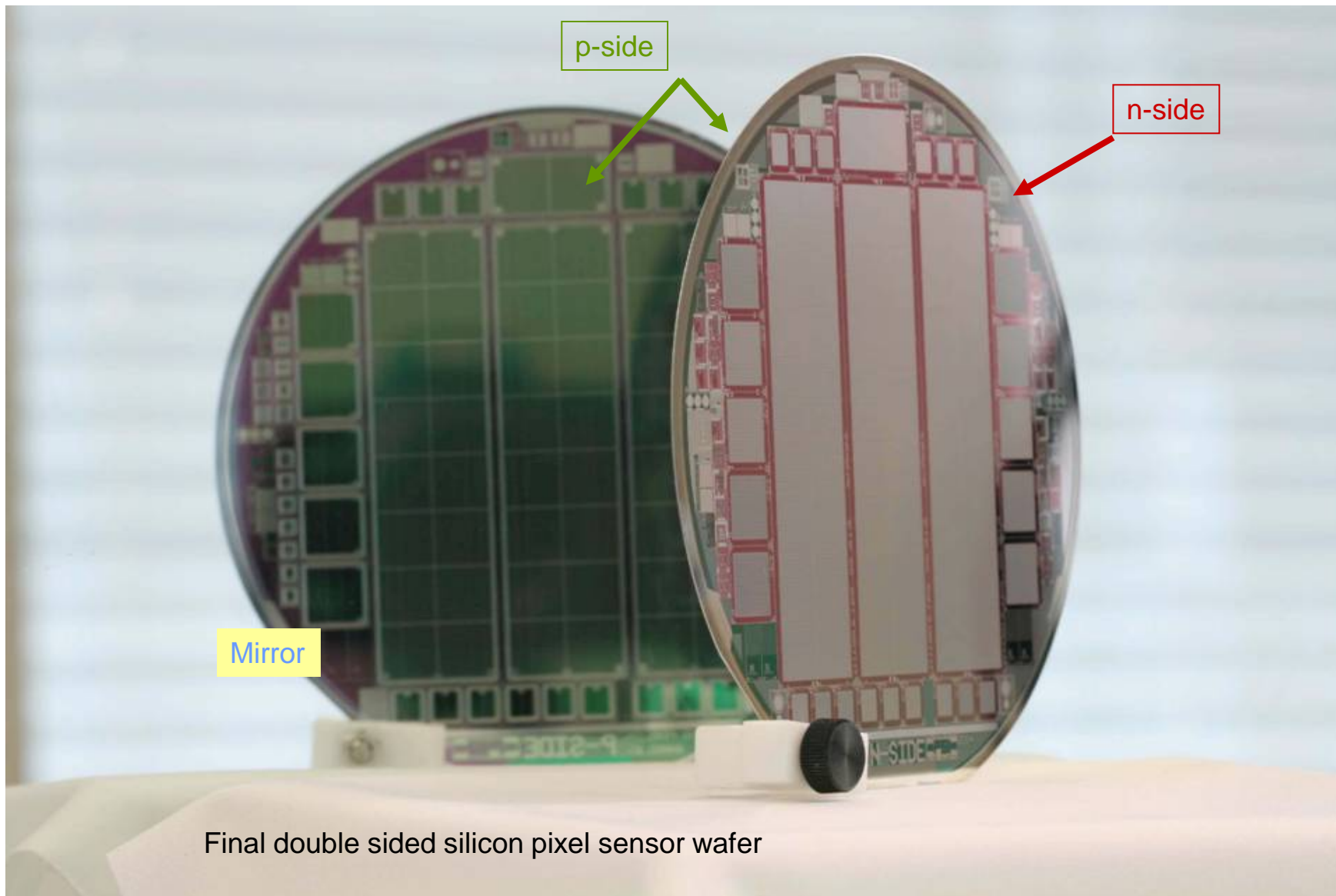


Depletion depth after LHC fluences



shallow angle technique

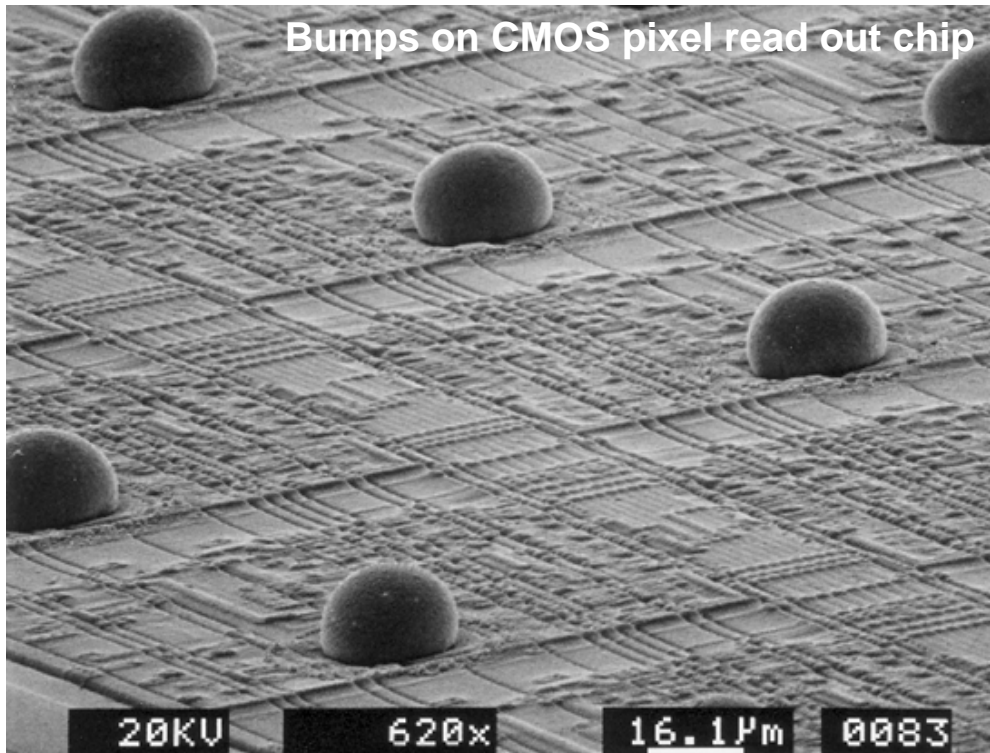
Now we need good 400 silicon sensor wafers



Final double sided silicon pixel sensor wafer

Micro – Bump bonding at PSI

- very dense 2-dimensional connection technique (typ. 10'000/cm²)
- **Key technology for Hybrid Pixel Detectors** (In 1996 commercially not available)
- 17μm Indium-bump balls to connect sensor to CMOS-ROC (Read Out Chip)

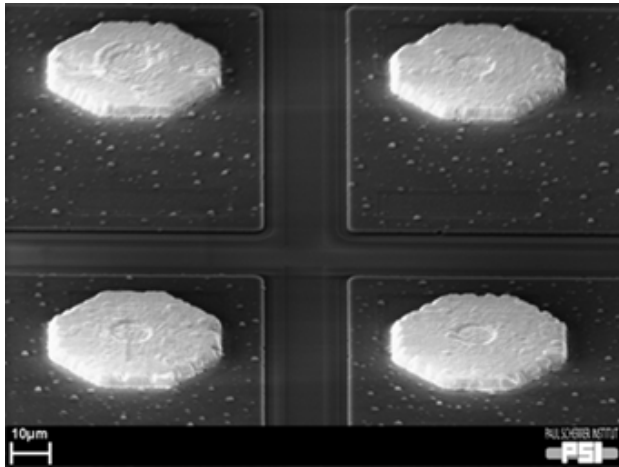


Silicon Pixel Sensor with Bumps

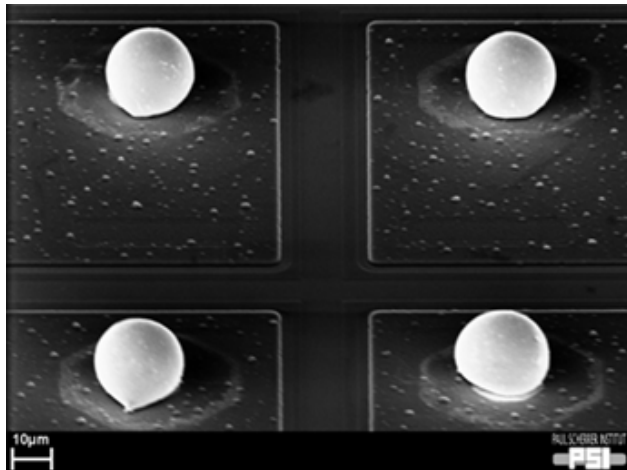


μ – Bump Process Steps

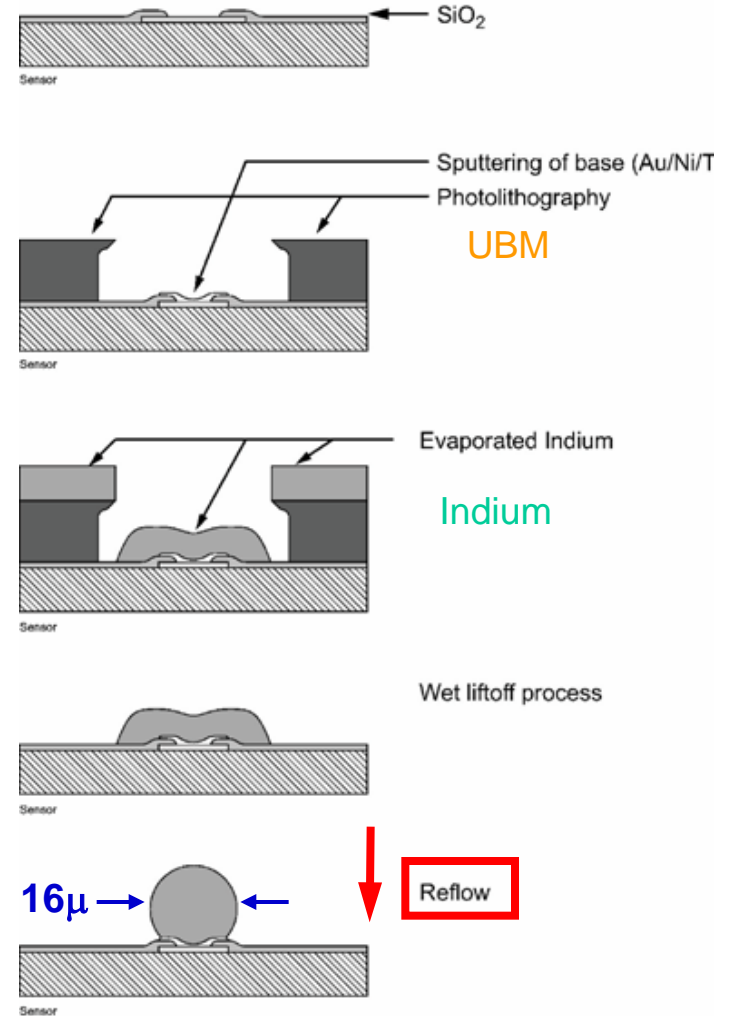
Indium “cakes” before reflow



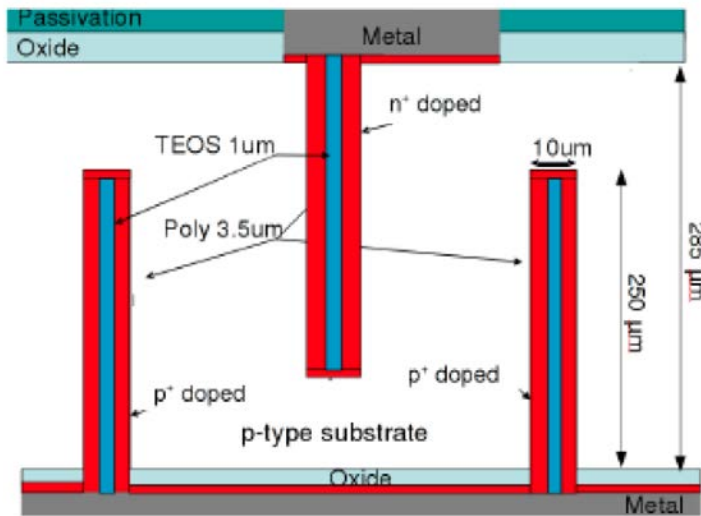
↓ reflow



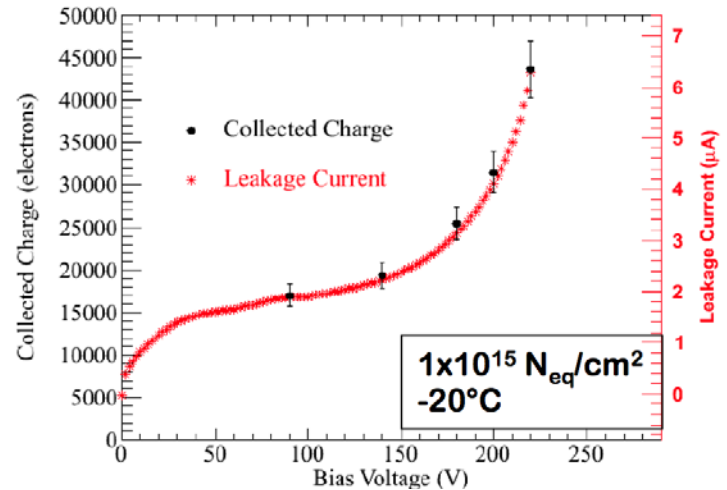
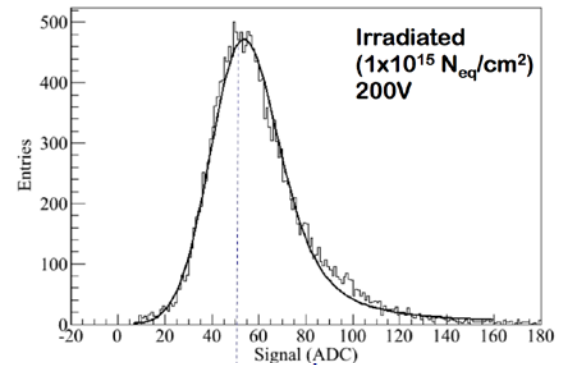
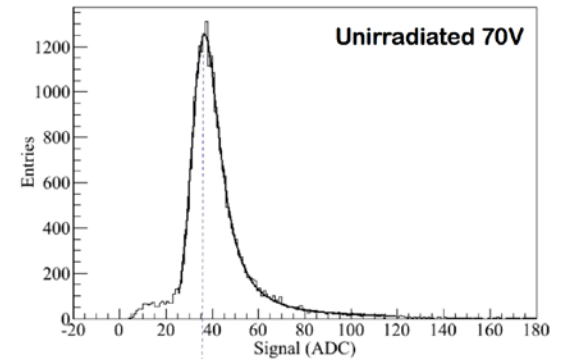
Indium balls after reflow



Charge Collection in 3D Detectors



- short charge collection distance
- insensitive regions for tracks passing through electrode pillars. e.g. 90° tracks
- interleaved electrode pillars \rightarrow capacitance !
- 3D sensors show avalanche charge multiplication after irradiation. (seen also in planar)
 - \rightarrow non gaussian sensor noise in read out

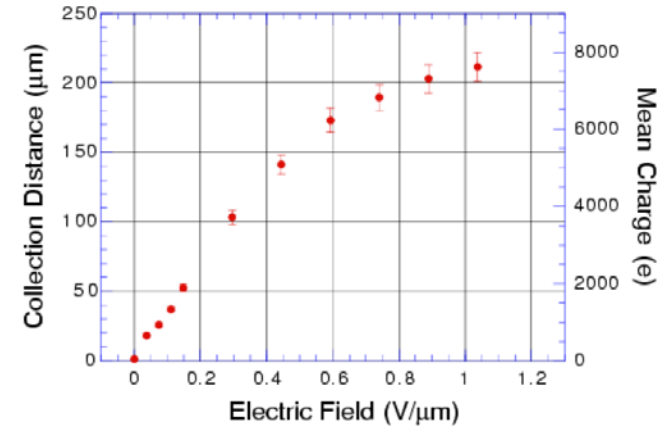
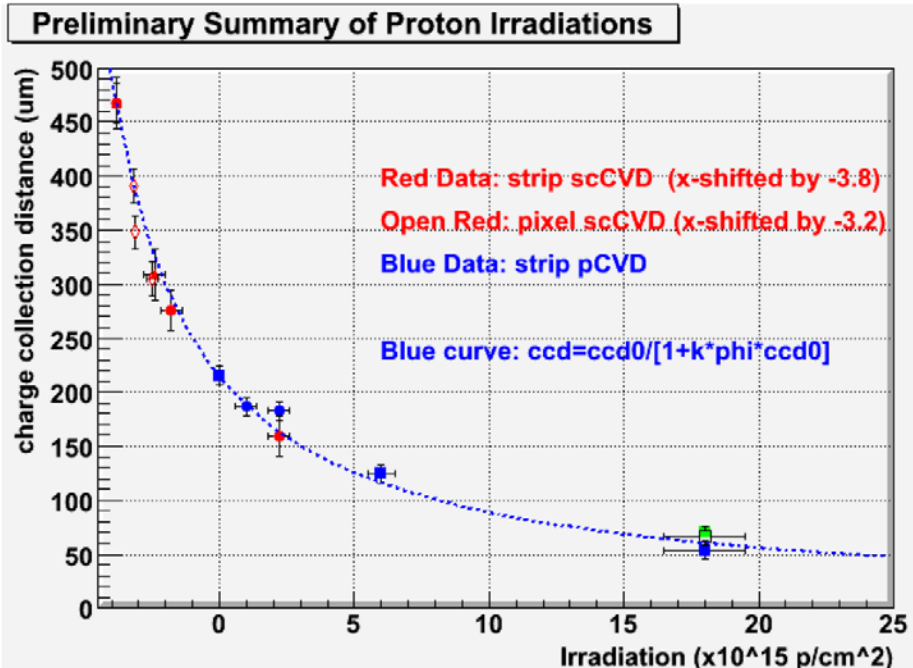


3D-silicon sensors planned in ATLAS ILB pixel upgrade

Diamond Sensors

- Diamond pixel sensor can be operated at 300^oK
- Excellent thermal conductor → heat removal
- Particle detectors from Chemical Vapor Deposited (CVD) Diamond are trapping defect dominated.
- Mono-crystalline diamonds show much better charge collection distances !

Mono- / Poly-crystalline Comparison



Poly-crystalline material shifted by $\approx 3.8 \times 10^{15}$ p/cm² to mono-crystalline material

Running construction projects:

- ATLAS Beam Conditions Monitor
- CMS Pixel Luminosity Telescope
- ATLAS Diamond Beam Monitor